

This Page Is Inserted by IFW Operations
and is not a part of the Official Record

BEST AVAILABLE IMAGES

Defective images within this document are accurate representations of the original documents submitted by the applicant.

Defects in the images may include (but are not limited to):

- BLACK BORDERS
- TEXT CUT OFF AT TOP, BOTTOM OR SIDES
- FADED TEXT
- ILLEGIBLE TEXT
- SKEWED/SLANTED IMAGES
- COLORED PHOTOS
- BLACK OR VERY BLACK AND WHITE DARK PHOTOS
- GRAY SCALE DOCUMENTS

IMAGES ARE BEST AVAILABLE COPY.

**As rescanning documents *will not* correct images,
please do not report the images to the
Image Problem Mailbox.**

THIS PAGE BLANK (USPTO)



INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(51) International Patent Classification 6 :
B65G 49/07

A1

(11) International Publication Number: WO 97/02199

(43) International Publication Date: 23 January 1997 (23.01.97)

(21) International Application Number: PCT/US96/11244

(22) International Filing Date: 2 July 1996 (02.07.96)

(30) Priority Data:

08/498,597	6 July 1995 (06.07.95)	US
08/499,069	6 July 1995 (06.07.95)	US
08/498,859	6 July 1995 (06.07.95)	US
08/498,987	6 July 1995 (06.07.95)	US

(71) Applicant: BROOKS AUTOMATION, INC. [US/US]; 15 Elizabeth Drive, Chelmsford, MA 01824 (US).

(72) Inventors: MUKA, Richard, S.; 32 Candlewood Drive, Topsfield, MA 01983 (US). PIPPINS, Michael, W.; 8 Gail Avenue, Hamilton, MA 01936 (US). DREW, Mitchell, A.; 400 Colonial Drive, Portsmouth, NH 03801 (US).

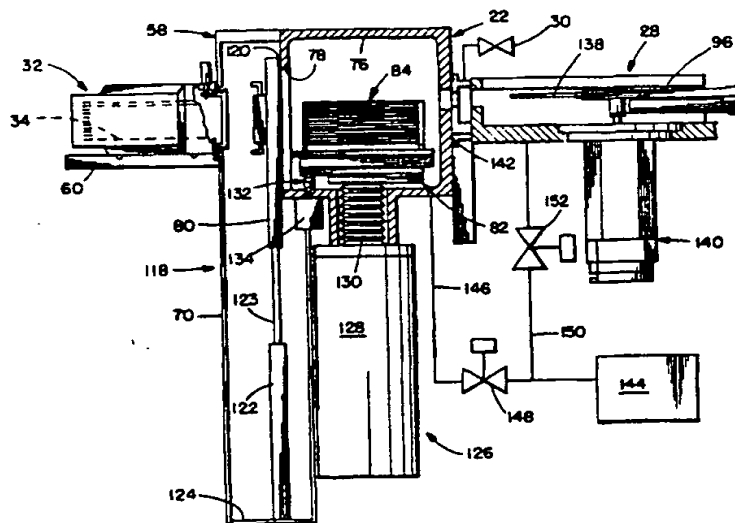
(74) Agent: GREEN, Clarence, A.; Perman & Green, 425 Post Road, Fairfield, CT 06430 (US).

(81) Designated States: AL, AM, AT, AU, AZ, BB, BG, BR, BY, CA, CH, CN, CZ, DE, DK, EE, ES, FI, GB, GE, HU, IL, IS, JP, KE, KG, KP, KR, KZ, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, TJ, TM, TR, TT, UA, UG, UZ, VN, ARIPO patent (KE, LS, MW, SD, SZ, UG), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG).

Published

With international search report.
With amended claims.

(54) Title: DOOR DRIVE MECHANISMS FOR SUBSTRATE CARRIER AND LOAD LOCK



(57) Abstract

A system is provided for batch loading semiconductor wafers into a load lock (22) from a portable carrier (32). The carrier is supported adjacent a load lock chamber. A multilevel end effector (84) associated with the load lock chamber includes a plurality of spaced end effector sets (92). The wafers are engaged and simultaneously retrieved as a grouping, then held in the load lock chamber for subsequent transport, one at a time, into an adjacent transport chamber (28). After transfer of the plurality of wafers from the carrier to the load lock chamber, the carrier and the load lock chamber are sealed and the load lock chamber and transport chambers are evacuated. A variety of mechanisms are provided for moving the end effector sets, and for moving a carrier door (44) and a load lock door (80) between closed and open positions and to a parked position. Mechanisms are also provided for individually moving a carrier door and a load lock door between closed and open positions and then, as a unit, to a parked position.

FOR THE PURPOSES OF INFORMATION ONLY

Codes used to identify States party to the PCT on the front pages of pamphlets publishing international applications under the PCT.

AM	Armenia	GB	United Kingdom	MW	Malawi
AT	Austria	GE	Georgia	MX	Mexico
AU	Australia	GN	Guinea	NE	Niger
BB	Barbados	GR	Greece	NL	Netherlands
BE	Belgium	HU	Hungary	NO	Norway
BF	Burkina Faso	IE	Ireland	NZ	New Zealand
BG	Bulgaria	IT	Italy	PL	Poland
BJ	Benin	JP	Japan	PT	Portugal
BR	Brazil	KE	Kenya	RO	Romania
BY	Belarus	KG	Kyrgyzstan	RU	Russian Federation
CA	Canada	KP	Democratic People's Republic of Korea	SD	Sudan
CF	Central African Republic	KR	Republic of Korea	SE	Sweden
CG	Congo	KZ	Kazakhstan	SG	Singapore
CH	Switzerland	LI	Liechtenstein	SI	Slovenia
CI	Côte d'Ivoire	LK	Sri Lanka	SK	Slovakia
CM	Cameroon	LR	Liberia	SN	Senegal
CN	China	LT	Lithuania	SZ	Swaziland
CS	Czechoslovakia	LU	Luxembourg	TD	Chad
CZ	Czech Republic	LV	Latvia	TG	Togo
DE	Germany	MC	Monaco	TJ	Tajikistan
DK	Denmark	MD	Republic of Moldova	TT	Trinidad and Tobago
EE	Estonia	MG	Madagascar	UA	Ukraine
ES	Spain	ML	Mali	UG	Uganda
FI	Finland	MN	Mongolia	US	United States of America
FR	France	MR	Mauritania	UZ	Uzbekistan
GA	Gabon			VN	Viet Nam

DOOR DRIVE MECHANISMS FOR SUBSTRATE CARRIER AND LOAD LOCKBACKGROUND OF THE INVENTION5 1. Field of the Invention:

10 The present invention relates to standardized mechanical interface systems for reducing particle contamination and more particularly to apparatus employing sealed containers suitable for use in semiconductor processing equipment to prevent particle contamination. Still more particularly, the invention relates to such systems enabling efficient transfer of semiconductor wafers between a transportable container or carrier and a load lock chamber with a controllable environment as they await further transfer to a processing station such as a cluster tool, or elsewhere. Throughput of the manufacturing process is thereby significantly increased.

20 Throughout this disclosure, the term "wafer" will be used for purposes of consistency to refer to planar substrates such as silicon wafers and glass flat panels, but it will be understood that it is intended to be used in the broad context so as to be applicable to all substrates. Typically, such substrates are circular and have a diameter of 200 mm and a thickness of approximately 0.760 mm although, more recently, the diameter of choice has evolved to 300 mm with the same thickness.

30 2. Description of the Prior Art

35 Control of particulate contamination is imperative for cost effective, high-yielding and profitable manufacturing of VLSI circuits. Because design rules increasingly call for smaller and smaller lines and spaces, it is necessary to exert greater and greater control on the number of particles and to remove particles with smaller and smaller diameters.

Some contamination particles cause incomplete etching in spaces between lines, thus leading to an unwanted electrical bridge. In addition to such physical defects, other contamination particles may cause electrical failure due to induced ionization or trapping centers in gate dielectrics or junctions.

The main sources of particulate contamination are personnel, equipment, and chemicals. Particles given off by personnel are transmitted through the environment and through physical contact or migration onto the wafer surface. People, by shedding of skin flakes, for example, are a significant source of particles that are easily ionized and cause defects.

Modern processing equipment must be concerned with particle sizes which range from below 0.01 micrometers to above 200 micrometers. Particles with these sizes can be very damaging in semiconductor processing. Typical semiconductor processes today employ geometries which are 1 micrometer and under. Unwanted contamination particles which have geometries measuring greater than 0.1 micrometer substantially interfere with 1 micrometer geometry semiconductor devices. The trend, of course, is to have smaller and smaller semiconductor processing geometries.

In the recent past, "clean rooms" were established in which through filtering and other techniques, attempts were made to remove particles having geometries of 0.03 micrometer and above. There is a need, however, to improve the processing environment. The conventional "clean room" cannot be maintained as particle free as desired. It is virtually impossible to maintain conventional clean rooms free of particles of a 0.01 micrometer size and below. Although clean room garments reduce particle emissions, they do not fully contain the emissions. It has been found that as many as 6000 particles per minute are emitted into

an adjacent one cubic foot of space by a fully suited operator.

To control contamination particles, the trend in the industry is to build more elaborate (and expensive) clean rooms with HEPA and ULPA recirculating air systems. Filter efficiencies of 99.999% and up to ten complete air exchanges per minute are required to obtain an acceptable level of cleanliness.

Particles within the equipment and chemicals are termed "process defects." To minimize process defects, processing equipment manufacturers must prevent machine generated particles from reaching the wafers, and suppliers of gases and liquid chemicals must deliver cleaner products. Most important, a system must be designed that will effectively isolate wafers from particles during storage, transport and transfer into processing equipment. The Standard Mechanical Interface (SMIF) system has been devised, and used, to reduce particle contamination by significantly reducing particle fluxes onto wafers. This end is accomplished by mechanically ensuring that during transport, storage and processing of the wafers, the gaseous media (such as air or nitrogen) surrounding the wafers is essentially stationary relative to the wafers and by ensuring that particles from the ambient outside environment do not enter the immediate internal wafer environment.

The SMIF concept is based on the realization that a small volume of still, particle-free air, with no internal source of particles, is the cleanest possible environment for wafers.

A typical SMIF system utilizes (1) minimum volume, dustproof boxes or carriers for storing and transporting (2) open rack wafer cassettes, and (3) doors on the boxes

or carriers designed to mate with doors on the interface ports on the processing equipment and the two doors being opened simultaneously so that particles which may have been on the external door surfaces are trapped ("sandwiched")
5 between the doors.

In a typical SMIF system, a box or carrier is placed at the interface port and latches release the box door and the port door simultaneously. A mechanical elevator lowers the
10 two doors, with the cassette riding on top. A manipulator picks up the cassette and places it onto the cassette port/elevator of the equipment. After processing, the reverse operation takes place.

15 SMIF systems have proved to be effective and this fact has been shown by experiments using SMIF components both inside and outside a clean room. The SMIF configuration achieved a ten-fold improvement over the conventional handling of open cassettes inside the clean room.

20 Using SMIF systems, it has been customary to carry a large number of the wafers within the box or carrier by supporting them in a spaced relationship by means of a cassette. Using this technique, the cassette is loaded
25 with a supply of wafers, transported into the box or carrier, then subsequently wafers are removed from the cassette in the carrier one by one for placement into a reception chamber at a cluster tool or other site of further processing. More recently, the cassette is being
30 replaced with yet more efficient devices for rapidly transporting multiple wafers at a time, yet in a particle free environment.

35 It was in light of the foregoing state of the art that the present invention has been conceived and is now reduced to practice. Specifically, the invention results from efforts to maintain clean room conditions for large numbers of

wafers being transported at a time while reducing equipment inventory and therefore initial cost, providing a simpler and more compact construction, reducing the cost of maintenance, and increasing throughput of processed items.

5 Much of the foregoing narrative has related to SMIF systems and the like for controlling the atmosphere within which the wafers reside during their handling operations. However, it will be appreciated that the invention herein may be broadly directed to the material handling aspects of

10 such systems without particular regard, in some instances, to the environment to which the wafers are exposed.

SUMMARY OF THE INVENTION

15 According to the invention, a system is provided for batch loading semiconductor wafers into a load lock from a portable carrier used for supporting a plurality of the wafers in spaced, stacked, relationship and transporting them, possibly in a particle free environment. The carrier

20 is supported adjacent a load lock chamber which may also have a particle free environment. A multilevel end effector associated with the load lock chamber includes a plurality of spaced end effector sets, each set being adapted to support a wafer thereon and aligned with an

25 associated wafer supported in the carrier. The wafers are engaged and simultaneously retrieved as a grouping, then held in the load lock chamber for subsequent transport, one at a time, into an adjacent transport chamber for delivery to a specified one of a plurality of processing stations of

30 a cluster tool. An isolation housing or mini-environment sealingly isolates the load lock chamber and the interior of the carrier from the surrounding atmosphere. After transfer of the plurality of wafers from the carrier to the load lock chamber, the carrier and the load lock chamber

35 are sealed and the load lock chamber and transport chambers are evacuated. A variety of mechanisms are provided for moving the end effector sets, both elevationally and into

and out of the carrier and load lock chamber, and for moving a carrier door and a load lock door between closed, sealed, positions and open positions and to a parked position remote from the region between the carrier and the load lock chamber. Mechanisms are also provided for individually moving a carrier door and a load lock door between closed, sealed, positions and open positions and then, as a unit, to a parked position remote from the region between the carrier and the load lock chamber.

10

The invention serves to interface a wafer carrier directly to a load lock while maintaining the clean environment of the substrate carrier. The invention results in an efficient, rapid operating, unified design which assures maximum throughput of processed wafers while protecting them from the outside environment throughout performance of the process steps.

15

No elevator is needed in the transfer of wafers since the load lock arm has a batch end effector which acts as a cassette in the load lock, yet has none of the constraints inherent in a cassette construction. Gaseous contamination from the cassette (typically a polymer which outgasses) is also eliminated thereby improving wafer process quality. Also, improved vacuum levels can be reached in shorter times since the arm assembly is primarily metal which outgasses minimally.

20

25

The invention results in a construction by reason of which the purposes of the carrier and cassette are unified while eliminating the need for a cassette and the inventory which is undesirably associated with the use of cassettes. The risk of exposing wafers to undesirable particle contamination present in moving air as in traditional SMIF loaders where the cassette is lowered from a SMIF box then transferred to a load lock is eliminated. In the instance of the invention, wafers are loaded in a batch

30

35

configuration which reduces overhead time and results in higher tool throughput.

5 Other and further features, advantages, and benefits of the invention will become apparent in the following description taken in conjunction with the following drawings. It is to be understood that the foregoing general description and the following detailed description are exemplary and explanatory but are not to be restrictive of the invention.

10 The accompanying drawings which are incorporated in and constitute a part of this invention, illustrate one of the embodiments of the invention, and, together with the description, serve to explain the principles of the invention in general terms. Like numerals refer to like

15 parts throughout the disclosure.

BRIEF DESCRIPTION OF THE DRAWINGS

In the drawings:

20

Fig. 1 is a top plan diagrammatic view of a wafer processing system embodying the present invention, with the cover removed from the transport chamber;

25 Fig. 2 is a diagrammatic side elevation view, certain parts being shown in section for clarity, illustrating in greater detail certain components illustrated in Fig. 1;

30 Fig. 3 is a diagrammatic detail side elevation view, certain parts being cut away and/or shown in section for clarity, illustrating in greater detail certain components illustrated in Fig. 2 and indicating the carrier door in its closed position;

35 Fig. 3A is a detail cross section view illustrating a small portion of Fig. 3;

Fig. 4 is a diagrammatic side elevation view illustrating a portion of Fig. 2 but indicating the carrier door in its open position;

5 Fig. 5 is a detail perspective view, certain parts being shown in section for clarity, illustrating in much greater detail components illustrated in Fig. 3;

10 Fig. 6 is a detail side elevation view illustrating a part of Fig. 2;

Fig. 7 is a cross section view taken generally along line 7--7 in Fig. 4;

15 Figs. 8, 9, 10, and 11 are diagrammatic side elevation views, similar to Fig. 4 but illustrating successive relative positions of the components thereof;

20 Fig. 12 is a detail perspective view illustrating in much greater detail components illustrated in Fig. 2;

Fig. 13 is a detail top plan view, largely in cross section, illustrating another embodiment of the invention;

25 Fig. 14 is a further detail top plan view, in cross section, illustrating a part of Fig. 13 in greater detail and illustrating components thereof in another position; and

30 Fig. 15 is a detail perspective view of parts illustrated in Fig. 14, certain parts being cut away and shown in section.

DETAILED DESCRIPTION OF THE PREFERRED EMBODIMENTS

35

Turn now to the drawings and, initially, to Fig. 1 which illustrates a processing system 20 for operating on silicon

planar substrates such as wafers and flat panels. As noted above, throughout the remainder of this disclosure, the term "wafer" will be used for purposes of consistency to refer to such substrates, but it will be understood that it is intended to be used in the broad context so as to be applicable to all substrates. The invention is especially beneficial for operating on the newer size of substrates.

The processing system 20 includes a load lock 22 for initially receiving wafers to be processed and a plurality of single-wafer processing stations 24 for operations on the surfaces of the wafers such as imaging, plasma etching, and the like. It is typical for the processing stations 24 to be arranged about a closed locus as indicated by a dashed line 26. A transport chamber 28 is disposed concentrically within the load lock 22 and processing stations 24 for singly transferring wafers to be processed and after processing between the load lock and one or more of the processing stations 24. A plurality of isolation valves 30 are individually provided at the interfaces of the several processing stations 24 and the transport chamber 28 and between the load lock 22 and the transport chamber 28.

As previously noted, for some time now, it has been known to employ transportable SMIF boxes or containers, herein referred to as "carriers", for maintaining articles, such as semiconductor wafers, clean. This has been achieved by maintaining within each carrier a substantially particle free environment while the wafers are being brought to, or removed from, the processing system 20. Previously, it was customary to carry a large number of the wafers within the carrier by supporting them in a spaced relationship by means of a cassette (not shown). Using this technique, the cassette would be loaded with a supply of wafers, transported into the carrier, then subsequently wafers would be removed from the cassette within the carrier one

by one for placement in the load lock 22 or the cassette would be transferred with the wafers within the clean mini-environment existing between the carrier, SMIF box, or the like, and the wafer processing equipment.

5

According to the invention, turning now to Figs. 2 and 3, a modified portable carrier 32 is provided for supporting and transporting a plurality of wafers 34 in spaced relationship in a substantially particle free environment. The carrier 32 has a plurality of rack member sets 36 for supporting the wafers generally horizontally, in a generally vertically spaced relationship.

10

The carrier 32 includes a carrier port 38 for providing access to the interior 40 thereof. A carrier door 42 on the carrier is movable between a closed position (Fig. 3) overlying the carrier port and an open position (Fig. 4) spaced from the carrier port. The carrier door 42 is illustrated as including a generally rectangular plate 44 and has a peripherally extending continuous transverse flange 46. A suitable seal 48 is interposed between the flange 46 and the carrier port 38 for sealing the interior 40 of the carrier from the surrounding atmosphere when the carrier door is in the closed position.

15

20

25

At least a pair of opposed locking tabs 50 extend in a direction toward the carrier 32 from the flange 46 and each locking tab has a hole 52 therethrough. Associated with each of the locking tabs 50 is a locking member 54 which may be in the form of a solenoid for operating a locking pin 56. Viewing especially Fig. 5, the locking member is suitably mounted on the carrier 32. When the locking pins 56 are engaged with their associated holes 52, the carrier door 42 is held closed with the flange 46 bearing firmly against the carrier port 38 with the seal 48 interposed between the flange and the port to maintain the particle free environment within the interior 40 of the carrier.

30

35

When the locking pins 56 are withdrawn from their associated holes 52, the carrier door 42 is then free to be removed from the carrier in a manner to be described below.

- 5 Also, according to the invention, an isolation housing or mini-environment 58 (see especially Fig. 2) is provided for sealingly isolating the load lock 22 and the interior 40 of the carrier 32 from the surrounding atmosphere. The carrier is brought in some suitable fashion from a remote
10 location, then placed on a platform 60 which is a part of the mini-environment 58 and projects in a direction away from the processing system 20. An upper surface 62 of the platform 60 is formed with a plurality of depressions 64 properly spaced to receive feet 66 which project from the
15 bottom of the carrier. When the feet 66 are fully engaged with the depressions 64, a front surface 68 of the carrier 32 is proximate an outer surface 70 of the mini-environment 58.
- 20 The mini-environment has an aperture 72 which is generally aligned with the load lock 22 but spaced therefrom and when the carrier is seated on the platform 60, the carrier door 42 projects through the aperture into the interior of the mini-environment. A suitable seal 74 is provided between
25 the mini-environment 58 and the carrier when supported on the platform and encompasses the carrier port 38 and the aperture 72 in the mini-environment for isolating the interior of the carrier, the interior of the mini-environment and the load lock from the surrounding
30 atmosphere. With the carrier 32 positioned on the platform 60 in the manner illustrated in Fig. 3, a plurality of clamps 300 (Fig. 3A) pivotally mounted on the outer surface 70 of the mini-environment 58 may be selectively operated to engage with associated clamp recesses 302 provided in
35 the outer peripheral surface of the carrier. In each instance, a clamp actuator 304 extends or retracts an actuator rod 306 which is pivotally attached to the clamp

300 at an end distant from the part engaging the recess 302. On signal, the clamp actuator 304 is effective to move the clamp 300 from the solid line position engaging the recess 302 to a broken line position disengaged from the recess. When all of the clamps 300 for the carrier 32 assume the solid line position, the seal 74 is compressed tightly between the carrier and the mini-environment.

The load lock 22 defines a chamber 76 therein having a substantially particle free environment and includes a load lock port 78 opening into the load lock chamber. As noted previously, the load lock 22 is positioned intermediate the carrier 32 and the transport chamber 28. A load lock door 80 is suitably mounted on the load lock for movement between a closed position overlying the load lock port 78 and an open position spaced therefrom.

A load lock arm 82 within the load lock chamber 76 is movable between an inactive position distant from the carrier 32 (see Fig. 2) and an active position proximate the carrier (see Fig. 3). The load lock arm and its operating mechanism may be of the construction disclosed in commonly assigned and copending application Serial No. _____, filed _____, entitled "Load Arm for Load Lock" [Perman & Green Docket No. 390-955938-NA], the disclosure of which is incorporated herein in its entirety, by reference.

With continuing reference to Figs. 3 and 4, and with new reference to Fig. 6, a multilevel end effector 84 is mounted on the load lock arm 82. As seen more clearly in Fig. 6, the multilevel end effector 84 includes a mounting manifold 86 which is suitably mounted on and projects upwardly from the load lock arm 82 and, more specifically, from an elongated joint 88 of an articulated pair of such joints 88, 90 pivotally mounted on the load lock arm. A plurality of vertically spaced end effector sets 92 are

integral with the mounting manifold and project outwardly from the mounting manifold in the direction of the carrier and lie in equally spaced parallel planes.

5 The spacing between the end effector sets 92 is substantially greater than the thickness of a wafer 34 for reasons which will become clear as this description proceeds. Each end effector set 92 includes a pair of
10 parallel laterally spaced end effector fingers 94 (see Fig. 7) which together are adapted to support a wafer in a generally horizontal plane. Each of the plurality of spaced end effector sets 92 is aligned with one of the rack member sets 36 when the load arm is in the active position and, therefore, with an associated wafer 34 supported in
15 the carrier. In order for movement of the multilevel end effector 84 toward and into the carrier 32 to commence in the manner about to be described, the load lock door 80 and the carrier door 42 must both be opened and moved to a remote location as seen in Fig. 8.

20 The multilevel end effector 84 is then movable, when the load lock arm 82 is in the active position, from a retracted position distant from the wafers to an advanced position within the interior 40 of the carrier 32 and
25 extending through the load lock port 78 and through the carrier port 38 for engaging and simultaneously retrieving the wafers as a grouping. The load lock arm 82 is operated in such a manner as to proceed to move the multilevel end effector 84 to the left (Fig. 9) with each of the end
30 effector sets 92 advancing beneath and out of engagement with its associated wafer 34. When the multilevel end effector 84 reaches its extreme leftward movement, the load lock arm, and with it the multilevel end effector 84, is raised a sufficient distance to lift the wafers, as a
35 grouping, off their associated spaced rack member sets. Thereupon, while retaining that elevated positioning, the load lock arm 82 is again operated, this time in such a

manner as to move the multilevel end effector 84 to the right, to the retracted position, for holding the grouping of the wafers 34 on the multilevel end effector 84 in the load lock chamber 76. See Fig. 11.

5

After the grouping of the wafers 34 is so positioned on the multilevel end effector 84 in the load lock chamber 76, a transport arm 96 within the transport chamber 28 may be operated for retrieving the wafers 34, one at a time, from
10 the multilevel end effector and delivering it to a specified one of the plurality of processing stations 24.

In order to operate the multilevel end effector 84 in the manner just described, it is necessary first to coordinate
15 the opening of the carrier door 42 and of the load lock door 80. The mechanism for achieving this coordinated operation will now be described. Initially, the carrier door is opened, then the load lock door is opened, then both doors together are moved to a location remote from
20 the region between the interior of the carrier and the load lock chamber.

The carrier door drive mechanism includes a coupling device 98 which is selectively engageable with the carrier door 42
25 and movable between a first position (Fig. 2) remote from the carrier door and adjacent the load lock door 80 and a second position (Fig. 3) adjacent the load lock door and remote from the load lock door. A first actuator 100 is mounted on the carrier door and, via a drive rod 102,
30 serves to move the coupling device 98 between the first and second positions. The coupling device includes a coupler frame 103 mounted on the drive rod and a pair of opposed axially aligned gripper members 104, 106 supported on and guided by the coupler frame. The gripper members 104, 106
35 include opposed axially aligned gripper rods 108 which are supported on and guided by the coupler frame 103 for movement between non-gripping positions and the gripping

positions. Specifically, each gripper member 104, 106 has a transverse gripper finger 110 at its terminal end, the gripper fingers being engaged with a peripheral rim 112 of the carrier door 42 when the gripper members are in their gripping positions.

Thus, the gripper fingers are movable between non-gripping positions (Fig. 3) free of engagement with the carrier door 42 and gripping positions (Fig. 4) in gripping engagement with the peripheral rim 112. Such gripping engagement of the carrier door by the gripper members 104, 106 can only occur when the coupling device 98 is in the first position. A second actuator 114 on the coupler frame 103 serves to move the gripper members 104, 106 between the non-gripping positions and the gripping positions via the suitably constrained gripper rods 108.

Proceeding through the operational sequence for opening the carrier door 42, operation of the first actuator 100 is initiated to move the coupling device 98 to the left to a location proximate the carrier door such that the gripper fingers 110 lie within the plane of the peripheral rim 112. Thereupon, operation of the second actuator 114 is initiated to move the gripping members radially until the gripping fingers firmly engage the peripheral rim 112. Thereupon, the first actuator 100 is again operated, this time to move the coupling device toward the right thereby causing an extremity 116 of the inwardly directed flange 46 to withdraw from the seal 48 which had, until now, maintained an environment isolated from the surrounding atmosphere. By means of the drive rod 102, the coupling device 98 and, with it, the carrier door 42 are moved to the right to a position adjacent the load lock door 80.

With the carrier door 42 so positioned adjacent the load lock door 80, a load lock door drive mechanism 118 is then operated for moving the load lock door and, with it, the

unit comprising the coupling device 98 and the carrier door 42 from the closed position to the open position. In the closed position, the load lock door 80 is held firmly against a suitable seal 120 interposed between the load lock door and the load lock 22 for isolating the load lock chamber 76 from the atmosphere (see Figs. 2 and 12). This may be achieved, for example, by means of spaced, opposed, generally vertically oriented guide channels 121 integral with the load lock 22 and provided on opposite sides of the load lock door 80.

The load lock door drive mechanism 118 includes a drive actuator 122 mounted on a base 124 of the mini-environment 58. The drive actuator 122 is vertically disposed with a drive actuator shaft 123 suitably attached to the load lock door 80 to move it between its raised closed position and a lowered open position remote from the region intermediate the carrier and the load lock chamber 76.

It will be appreciated that operation of the multilevel end effector 84 cannot be achieved until the drive mechanism 118 has been operated to move the load lock door, the coupling device 98, and the carrier door 42 all to the lowered position as indicated in Fig. 8.

An index drive mechanism 126 is provided for moving the load lock arm between the inactive position (Fig. 11) and the active position (Fig. 10). As previously mentioned, the load lock arm 82 and its operating mechanism, herein the index drive mechanism 126, may be of the construction disclosed in commonly assigned and copending application Serial No. _____, filed _____.

The index drive mechanism 126 includes a suitable index actuator 128 which is of the type which can advance an index actuator shaft 130, as desired, either in a macro fashion rapidly over a relatively long distance or in a

micro fashion, that is, in incremental steps. Thus, the index actuator, in one mode of operation, can move the load lock arm between an active position (Figs. 8-10) at which all of the end effector sets 92 are aligned with their associated rack member sets 36 in the interior 40 of the carrier 42 and an inactive position (Fig. 11) at which all of the end effector sets are not so aligned with their associated rack member sets. In the former instance, a clutch 132 is engaged; in the latter instance, the clutch is disengaged.

An arm drive mechanism 134 includes a suitable rotary actuator 136 for moving the load lock arm 82 and, with it, the multilevel end effector 84 between the retracted and advanced positions. The arm drive mechanism 134 further includes engageable clutch elements 132a and 132b which only engage when the index drive mechanism moves the load lock arm and the multilevel end effector to the active position. When that occurs, the end effector 84 can be advanced into the interior of the carrier as previously described.

It was previously mentioned that a transport arm 96 within the transport chamber 28 may be operated for retrieving the wafers 34, one at a time, from the multilevel end effector and delivering it to a specified one of the plurality of processing stations 24. The index drive mechanism 126 may also be operated in its incremental mode to adjust the level of a particular end effector set 92 with robot end effector fingers 138 on the transport arm 96 within the transport chamber 28. In this manner, with the clutch elements 132a, 132b disengaged, the transport arm 96 driven by a transport actuator 140 is effective to retrieve wafers one at a time from the multilevel end effector 84 for delivery to a specified one of the processing stations 24. The transport arm 96 and its associated transport actuator 140 may be of the construction disclosed in commonly

assigned U.S. Patent No. 5,180,276 to Hendrickson, the disclosure of which is incorporated herein in its entirety, by reference.

5 A suitable isolation valve 30, previously mentioned, is provided intermediate the load lock chamber 76 and the transport chamber 28. The isolation valve is sufficiently large to permit passage therethrough of the robot end effector fingers supporting a wafer 34 and is selectively operable to permit fluid intercommunication between the load lock chamber and the transport chamber in one instance and to prevent fluid intercommunication therebetween. Of course, failure to permit fluid intercommunication between the chambers also results in prevention of passage therethrough of the robot end effector fingers supporting a wafer 34. Additionally, a suitable seal 142 is interposed between the load lock 22 and the transport chamber 28 for isolating the load lock and the transport chamber from the surrounding atmosphere when the isolation valve is positioned to permit fluid intercommunication between the load lock chamber and the transport chamber.

A source of vacuum 144 is provided for selectively evacuating the load lock chamber 76 and the transport chamber 28. A conduit 146 extends between the source of vacuum 144 and the load lock chamber and a selectively operable valve 148 in the conduit 146 interconnects the vacuum source and the load lock chamber 76 when the load lock door 80 is closed and disconnects the vacuum source from the load lock chamber when the load lock door is open. In a similar manner, a conduit 150 extends between the source of vacuum 144 and the transport chamber. A selectively operable valve 152 in the conduit 150 interconnects the vacuum source and the transport chamber when the transport chamber is isolated from the surrounding atmosphere.

Turn now to Figs. 13-15 for a description of another, and preferred, embodiment 160 of the carrier door drive mechanism. In this instance, a carrier 162 is similar to the carrier 32 previously described for supporting and transporting a plurality of wafers 34 in spaced generally stacked relationship. As before, the carrier 162 has a carrier port 164 for providing access to its interior 166. Again, there is a mini-environment 168 for sealingly isolating the load lock chamber and the interior of the carrier from the surrounding atmosphere. Again, the carrier 162 includes a carrier door 170 which is movable between a closed position overlying the carrier port 164 for sealing the interior 166 from the surrounding atmosphere and an open position spaced from the carrier port.

A load lock door 172 on the load lock is movable in the manner previously described between a closed position overlying the load lock port for sealing the load lock chamber from the surrounding atmosphere and an open position spaced therefrom. The carrier door drive mechanism and its operation are also as previously described.

The mini-environment 168 has an aperture generally aligned with the load lock port but spaced therefrom and includes the platform 60 for supporting the carrier 162 thereon such that the carrier port 164 is proximate the aperture 174 in the mini-environment. A suitable seal 176 is provided between the mini-environment and the carrier when the carrier is supported on the platform and encompasses the carrier port and the aperture in the mini-environment for isolating the interior of the carrier, the interior of the mini-environment and the load lock chamber from the surrounding atmosphere.

The carrier door drive mechanism 160 includes a coupling

mechanism 178 which is selectively engageable with the carrier door 170 and movable between a first position remote from the carrier and adjacent the load lock door and (as depicted by broken lines in Fig. 13) and a second position adjacent the carrier door and remote from the load lock door (as depicted by solid lines in Fig. 13). A first actuator 180 is mounted on the load lock door 172 and includes a drive rod 182 for moving the coupling mechanism 178 between the first and second positions.

The carrier door 170 is recessed as at 184 (Figs. 14 and 15) and has a gripper slot 186 therein. The coupling mechanism 178 includes a door gripper plate 188 mounted on the drive rod 182 and matingly receivable with the carrier port 164 when the coupling mechanism is in the second position as mentioned earlier. A door gripper bar 190 on a second actuator 192 which, in turn, is mounted on the door gripper plate 188 has a pair of bent fingers 194 at a distal end thereof movable between a gripping position grippingly engaging the gripper slot 186 in the carrier door 170 and a release position disengaged therefrom.

Additionally, a latch mechanism 196 is provided on the carrier door for selective engagement with the carrier for securely attaching the carrier door to the carrier. For this purpose, the carrier 162 has a latch recess 198 (Fig. 14) in the carrier port 164. Cooperating with the latch recess 198, the latch mechanism 196 includes a latch 200 pivotally mounted, as at 201, on the carrier door 170 for movement between a latching position engaged with the latch recess and an unlatching position disengaged from the latch recess. A retention pin 202 is pivotally connected to the latch at a first end 204 within the recess 184 and has a second turned end 206 opposite the first end. The turned end 206 is receivable in a slot 208 between the pair of bent fingers 194 and is engageable with the door gripper bar 190.

A compression spring 210 encircles the retention pin 202 and is suitably supported within the recess 184 for biasing the latch 200 to the latching position. At its left end (viewing Figs. 14 and 15) the spring is seated against
5 opposed shoulder members 212 which project into the recess from opposite walls of the recess 198 in the carrier door 170. The right end of the spring 210 bears against a c-clamp 214 fixed to the retention pin 202 an appropriate distance from the shoulder members 212. With this
10 construction, the retention pin and its second, turned, end 206 is biased toward the right, viewing Figs. 13-15. In this manner, the spring 210 is effective to hold the latch 200 in a normally closed position in engagement with the latch recess 198. However, the movement of the door
15 gripper bar 190 to move the pair of bent fingers 194 into the gripping position grippingly engaging the gripper slot 186 is effective to simultaneously move the latch to the unlatching position disengaged from the latch recess. With continued operation of the actuator 192 to hold the bent
20 fingers 194 in engagement with the gripper slot 186 and to hold the latch 200 swung in the open position (all as shown in Fig. 14), the carrier door 170 and the door gripper plate 188 operate as a unit and can be moved by the actuator 180 to the open, broken line, position indicated
25 in Fig. 13.

While preferred embodiments of the invention have been disclosed in detail, it should be understood by those skilled in the art that various other modifications may be
30 made to the illustrated embodiments without departing from the scope of the invention as described in the specification and defined in the appended claims.

CLAIMS

What is claimed is:

1. In combination with a system for batch loading semiconductor wafers including a portable carrier for supporting and transporting in a substantially particle free environment a plurality of the wafers in spaced generally stacked relationship, said carrier having a carrier port for providing access to the interior thereof, a load lock defining a chamber therein having a substantially particle free environment and including a load lock port opening into the load lock chamber, and an isolation housing for sealingly isolating the load lock chamber and the interior of the carrier from the surrounding atmosphere, a communication access assembly comprising:

a carrier door on said carrier movable between a closed position overlying said carrier port for sealing the interior of said carrier from the surrounding atmosphere and an open position spaced from said carrier port;

a load lock door on said load lock movable between a closed position overlying said load lock port for sealing the load lock chamber from the surrounding atmosphere and an open position spaced therefrom;

a carrier door drive mechanism on said load lock door for moving said carrier door between the closed and open positions;

said isolation housing having an aperture generally aligned with said load lock port but spaced therefrom and including a platform for supporting said carrier thereon such that said carrier port is proximate the

aperture in said isolation housing; and

seal means between said isolation housing and said carrier when said carrier is supported on said platform and encompassing said carrier port and the aperture in said isolation housing for isolating the interior of said carrier, the interior of said isolation housing and the load lock chamber from the surrounding atmosphere.

2. The combination as set forth in claim 1

wherein said carrier door drive mechanism includes:

coupling means selectively engageable with said carrier door and movable between a first position remote from said carrier and adjacent said load lock door and a second position adjacent said carrier door and remote from said load lock door;

a first actuator for moving said coupling means between said first and second positions;

said coupling means including gripper members movable between non-gripping positions free of engagement with said carrier door and gripping positions in gripping engagement with said carrier door when said coupling means is in said first position; and

a second actuator for moving said gripper members between the non-gripping positions and the gripping positions.

3. The combination as set forth in claim 2

wherein said carrier door has a peripheral rim;

wherein said first actuator includes a drive rod for moving said coupling means between said first and second positions;

wherein said coupling means includes a coupler frame mounted on said drive rod; and

wherein said gripper members include opposed axially aligned gripper rods supported on and guided by said coupler frame for movement between the non-gripping positions and the gripping positions, each said gripper member having a transverse gripper finger at its terminal end, said gripper fingers being engaged with said peripheral rim when said gripper members are in their gripping positions.

4. The combination as set forth in claim 1 including:

a load lock door drive mechanism for moving said load lock door between the closed and open positions.

5. The combination as set forth in claim 3 including:

a load lock door drive mechanism for moving said load lock door between the closed position coextensive with said load lock port and an open position distant therefrom, and for simultaneously moving as a unit with said load lock door said coupling means and said carrier door integral therewith upon movement of said gripper members to their gripping positions in engagement with said rim of said carrier door and upon movement of said coupling means to the first position.

6. The combination as set forth in claim 2

including:

wherein said carrier door is recessed and has a gripper slot therein;

wherein said first actuator includes a drive rod for moving said coupling means between said first and second positions;

wherein said coupling means includes:

a door gripper plate mounted on said drive rod and matingly receivable with said carrier port when said coupling means is in the second position; and

a door gripper bar on said second actuator and having pair of bent fingers at a distal end thereof movable between a gripping position grippingly engaging the gripper slot in said carrier door and a release position disengaged therefrom.

7. The combination as set forth in claim 6 including:

latch means on said carrier door selectively engageable with said carrier for securely attaching said carrier door to said carrier.

8. The combination as set forth in claim 7

wherein said carrier has a latch recess in said carrier port;

wherein said latch means includes:

a latch pivotally mounted on said carrier door for movement between a latching position engaged with sa

latch recess and an unlatching position disengaged from said latch recess;

a retention pin pivotally connected to said latch a first end within said carrier door and having a second turned end opposite said first end, said turned end receivable between said pair of bent fingers and engageable with said door gripper bar; and

resilient means biasing said latch to the latching position;

whereby movement of said door gripper bar to move said pair of bent fingers into the gripping position grippingly engaging the gripper slot in said carrier door is effective to simultaneously move said latch to the unlatching position disengaged from said latch recess.

9. The combination as set forth in claim 5 including:

a load lock door drive mechanism for moving said load lock door between the closed position coextensive with said load lock port and an open position distant therefrom, and for simultaneously moving as a unit with said load lock door said coupling means and said carrier door integral therewith upon movement of said gripper members to their gripping positions in engagement with said rim of said carrier door and upon movement of said coupling means to the first position.

10. A system for batch loading semiconductor wafers comprising:

a portable carrier for supporting and transporting in

a substantially particle free environment a plurality of the wafers in spaced generally stacked relationship, said carrier having a carrier port for providing access to the interior thereof;

a load lock defining a chamber therein having a substantially particle free environment and including a load lock port opening into the load lock chamber;

means for sealingly isolating the load lock chamber and the interior of the carrier from the surrounding atmosphere; and

a multilevel end effector in said load lock including a plurality of spaced end effector sets, each said end effector set adapted to support a wafer thereon, each of said plurality of spaced end effector sets being aligned with an associated wafer supported in the carrier when said load lock arm is in the active position, said multilevel end effector being movable from a retracted position distant from the wafers to an advanced position extending through said load lock port and through said carrier port into the carrier for engaging and simultaneously retrieving the wafers as a grouping, then again to the retracted position, holding the grouping of wafers in the load lock chamber.

11. A system for batch loading semiconductor wafers comprising:

a portable carrier for supporting and transporting in a substantially particle free environment a plurality of the wafers in spaced substantially spaced relationship, said carrier having a carrier port for providing access to the interior thereof;

a carrier door on said carrier movable between a closed position overlying said carrier port for sealing the interior of said carrier from the surrounding environment and an open position spaced from said carrier port;

a load lock defining a chamber therein having a substantially particle free environment and including a load lock port opening into the load lock chamber;

a load lock door on said load lock movable between a closed position overlying said load lock port and an open position spaced therefrom;

a load lock arm within the load lock chamber movable between an inactive position distant from the carrier and an active position proximate the carrier; and

a multilevel end effector on said load lock arm including a plurality of spaced end effector sets, each said end effector set adapted to support a wafer thereon, each of said plurality of spaced end effector sets being aligned with an associated wafer supported in the carrier when said load lock arm is in the active position, said multilevel end effector being movable, when said load lock arm is in the active position and when said load lock door is in the open position, from a retracted position distant from the wafers to an advanced position within the carrier and extending through said load port and through said carrier port for engaging and simultaneously retrieving the wafers as a grouping, then again to the retracted position for holding the grouping of the wafers in the load lock chamber.

12. A system as set forth in claim 11

wherein said carrier has a plurality of spaced rack member sets for supporting the wafers, each of said plurality of spaced end effector sets being aligned with an associated one of said rack member sets when said load arm is in the active position.

13. A system as set forth in claim 11

wherein each said end effector set is positioned for generally horizontally supporting a wafer thereon; and

wherein said plurality of said rack member sets in said carrier are vertically spaced for reception of the wafers thereon in a stacked relationship.

14. A system as set forth in claim 11

including:

an arm drive mechanism for moving said load lock arm between the inactive position and the active position; and

an end effector drive mechanism for moving said multilevel end effector between the retracted and advanced positions.

15. A system as set forth in claim 11 including:

a load lock door drive mechanism for moving said load lock door between the closed and open positions.

16. A system as set forth in claim 11 including:

a carrier door drive mechanism on said load lock door for moving said carrier door between the closed and

open positions when said load lock door is in the closed position.

17. A system as set forth in claim 14 including:

a load lock door drive mechanism for moving said load lock door between the closed and open positions; and

a carrier door drive mechanism on said load lock door for moving said carrier door between the closed and open positions when said load lock door is in the closed position.

18. A system as set forth in claim 11 including:

an isolation housing for sealingly isolating the load lock chamber and the interior of the carrier from the surrounding atmosphere.

19. A system as set forth in claim 18

wherein said isolation housing has an aperture generally aligned with said load lock port but spaced therefrom and includes a platform for supporting said carrier thereon such that said carrier port is proximate the aperture in said isolation housing; and

including:

seal means between said isolation housing and said carrier when supported on said platform and encompassing said carrier port and the aperture in said isolation housing for isolating the interior of said carrier, the interior of said isolation housing and the load lock chamber from the surrounding atmosphere.

20. A system as set forth in claim 11 including:

seal means between said load lock door and said load lock for isolating the load lock chamber from the atmosphere when said load lock door is in the closed position.

21. A system for batch loading semiconductor wafers comprising:

a portable carrier for supporting and transporting a plurality of the wafers in spaced substantially spaced relationship, said carrier having a carrier port for providing access to the interior thereof;

a carrier door on said carrier movable between a closed position overlying said carrier port and an open position spaced from said carrier port;

a load lock defining a chamber therein and including a load lock port opening into the load lock chamber;

a load lock door on said load lock movable between a closed position overlying said load lock port and an open position spaced therefrom;

a load lock arm within the load lock chamber movable between an inactive position distant from the carrier and an active position proximate the carrier;

a multilevel end effector on said arm for moving the plurality of wafers as a grouping between said carrier and the load lock chamber; and

a coordinated door opening drive mechanism for sequentially opening said carrier door and said load lock door when said arm is in the active position.

22. A system as set forth in claim 21

wherein said multilevel end effector includes a plurality of spaced end effector sets, each said end effector set adapted to support a semiconductor wafer thereon, each of said plurality of spaced end effector sets being aligned with an associated wafer supported in said carrier when said arm is in the active position, said multilevel end effector being movable, when said arm is in the active position, from a retracted position distant from the wafers to an advanced position within said carrier for engaging and simultaneously retrieving the wafers as a grouping, then again to the retracted position while holding the grouping of wafers and, when said arm is in the inactive position, each of said plurality of spaced end effector sets being out of alignment with an associated wafer supported in said carrier and said multilevel end effector being incapable of movement when said arm is in the inactive position.

23. A system as set forth in claim 21

wherein said coordinated door opening drive mechanism includes means for sequentially moving said carrier door and said load lock door as a unit from a location generally coextensive with said carrier port and with said load lock port to a location distant therefrom.

24. A system for batch loading semiconductor wafers to and from a carrier used for supporting and transporting in a substantially particle free environment a plurality of the wafers in spaced generally stacked relationship, said system comprising:

a load lock defining a chamber therein having a

substantially particle free environment and including a load lock port opening into the load lock chamber;

a load lock door on said load lock movable between a closed position sealingly overlying said load lock port and an open position spaced therefrom;

a load lock arm within the load lock chamber movable between an inactive position distant from the carrier and an active position proximate the carrier; and

a multilevel end effector on said load lock arm including a plurality of spaced end effector sets, each said end effector set adapted to support a wafer thereon, each of said plurality of spaced end effector sets being aligned with an associated wafer supported in the carrier when said load lock arm is in the active position, said multilevel end effector being movable, when said load lock arm is in the active position and when said load lock door is in the open position, from a retracted position distant from the wafers to an advanced position within the carrier for engaging and simultaneously retrieving the wafers as a grouping, then again to the retracted position for holding the grouping of wafers in the load lock chamber.

25. A system as set forth in claim 24 including:

an arm drive mechanism for moving said load lock arm between the inactive position and the active position; and

an end effectuator drive mechanism for moving said multilevel end effector between the retracted and advanced positions.

26. A system as set forth in claim 25 including:

an isolation housing for sealingly isolating the load lock chamber and the interior of the carrier from the surrounding atmosphere.

27. A system as set forth in claim 24 including:

seal means between said load lock door and said load lock for isolating the load lock chamber from the surrounding atmosphere when said load lock door is in the closed position.

28. A system as set forth in claim 24 including:

a load lock door drive mechanism for moving said load lock door between the closed and open positions.

29. A system as set forth in claim 24 including:

vacuum means for selectively evacuating the load lock chamber when said load lock door is in the closed position;

a source of vacuum;

conduit means extending between said source of vacuum and said transfer chamber;

selectively operable valve means in said conduit means for interconnecting said vacuum source and said transfer chamber when said transfer chamber is isolated from the surrounding atmosphere.

30. A system for handling a plurality of semiconductor wafers supported in spaced, generally stacked, relationship comprising:

arm means movable between an active position and an inactive position distant from the active position;

a multilevel end effector on said arm means including a plurality of spaced end effector sets, each said end effector set adapted to support a semiconductor wafer thereon, each of said plurality of spaced end effector sets being aligned with an associated wafer supported in a carrier when said arm means is in the active position, said multilevel end effector being movable, when said arm means is in the active position, from a retracted position distant from the wafers to an advanced position within the carrier for engaging and simultaneously retrieving the wafers as a grouping, then again to the retracted position while holding the grouping of wafers and, when said arm means is in the inactive position, each of said plurality of spaced end effector sets being out of alignment with an associated wafer supported in a carrier and said multilevel end effector being incapable of movement when said arm means is in the inactive position.

31. A system for handling semiconductor wafers as set forth in claim 30 including:

arm drive means for moving said arm means between the active position and the inactive position.

32. A system for handling semiconductor wafers as set forth in claim 30

wherein said arm drive means includes index drive means for incrementally moving said multilevel end effector in order to locate a selected one of said plurality of end effector sets at a predetermined position for removal therefrom of the individual wafer supported thereon.

33. A system for batch loading semiconductor wafers comprising:

- 5 a portable carrier for supporting and transporting in a substantially particle free environment a plurality of the wafers in spaced generally stacked relationship, said carrier having a carrier port for providing access to the interior thereof;
- 10 a plurality of rack members for supporting a plurality of the wafers in spaced relationship within said carrier;
- 15 a carrier door on said carrier movable between a closed position overlying said carrier port for sealing the interior of said carrier from the surrounding atmosphere and an open position spaced from said carrier port;
- 20 a transport chamber for receiving wafers for transfer to a plurality of processing stations;
- 25 a load lock defining a chamber therein having a substantially particle free environment and including a load lock port opening into the load lock chamber, said load lock positioned intermediate said carrier and said transport chamber;
- 30 a load lock door on said load lock movable between a closed position overlying said load lock port and an open position spaced therefrom;
- 35 a load lock arm within the load lock chamber movable between an inactive position distant from said carrier and an active position proximate said carrier;
- a multilevel end effector on said load lock arm

including a plurality of spaced end effector sets, each said end effector set adapted to support a wafer thereon, each of said plurality of spaced end effector sets being aligned with an associated wafer supported in said carrier when said load lock arm is in the active position, said multilevel end effector being movable, when said load lock arm is in the active position, from a retracted position distant from the wafers to an advanced position within said carrier and extending through said load port and through said carrier port for engaging and simultaneously retrieving the wafers as a grouping, then again to the retracted position for holding the grouping of wafers in the load lock chamber; and

a transport arm within said transport chamber for retrieving wafers one at a time from said multilevel end effector and delivering it to a specified one of the plurality of processing stations.

34. A system as set forth in claim 33

wherein said carrier has a plurality of spaced rack member sets for supporting the wafers, each of said plurality of spaced end effector sets being aligned with an associated one of said rack member sets when said load arm is in the active position.

35. A system as set forth in claim 33

wherein each said end effector set is positioned for horizontally supporting a wafer thereon; and

wherein said plurality of said rack member sets in said carrier are vertically spaced for reception of the wafers thereon in a stacked relationship.

36. A system as set forth in claim 33

including:

- 5 an arm drive mechanism for moving said load lock arm
 between the inactive position and the active position;
 and
- 10 an end effector drive mechanism for moving said
 multilevel end effector between the retracted and
 advanced positions.

37. A system as set forth in claim 33 including:

- 15 a load lock door drive mechanism for moving said load
 lock door between the closed and open positions.

38. A system as set forth in claim 33 including:

- 20 a carrier door drive mechanism on said load lock door
 for moving said carrier door between the closed and
 open positions when said load lock door is in the
 closed position.

25 39. A system as set forth in claim 36 including:

- a load lock door drive mechanism for moving said load
 lock door between the closed and open positions; and
- 30 a carrier door drive mechanism on said load lock door
 for moving said carrier door between the closed and
 open positions when said load lock door is in the
 closed position.

35 40. A system as set forth in claim 33 including:

- an isolation housing for sealingly isolating the load

lock chamber and the interior of the carrier from the surrounding atmosphere.

41. A system as set forth in claim 40

5

wherein said isolation housing has an aperture generally aligned with said load lock port but spaced therefrom and includes a platform for supporting said carrier thereon such that said carrier port is proximate the aperture in said isolation housing; and

10

including:

seal means between said isolation housing and said carrier when supported on said platform and encompassing said carrier port and the aperture in said isolation housing for isolating the interior of said carrier, the interior of said isolation housing and the load lock chamber from the surrounding atmosphere.

15

20

42. A system as set forth in claim 33 including:

seal means between said load lock door and said load lock for isolating the load lock chamber from the atmosphere when said load lock door is in the closed position.

25

43. A system as set forth in claim 33 including:

30

seal means between said load lock door and said load lock for isolating the load lock chamber from the surrounding atmosphere when said load lock door is in the closed position.

35

44. A system as set forth in claim 33 including:

isolation valve means intermediate the load lock chamber and said transport chamber selectively operable to permit fluid intercommunication therebetween in one instance and to prevent fluid intercommunication therebetween in another instance; and

seal means between said load lock and said transfer chamber for isolating said load lock and said transfer chamber from the surrounding atmosphere when said isolation valve means is positioned to permit fluid intercommunication between the load lock chamber and said transfer chamber.

45. A system as set forth in claim 33 including:

a source of vacuum;

conduit means extending between said source of vacuum and the load lock chamber;

selectively operable valve means in said conduit means for interconnecting said vacuum source and the load lock chamber when said load lock door is closed and for disconnecting said vacuum source from the load lock chamber when said load lock door is open.

46. A system as set forth in claim 33 including:

a source of vacuum;

conduit means extending between said source of vacuum and said transfer chamber;

selectively operable valve means in said conduit means for interconnecting said vacuum source and said transfer chamber when said transfer chamber is

isolated from the surrounding atmosphere.

47. A system as set forth in claim 38

5 wherein said carrier door drive mechanism includes:

coupling means selectively engageable with said
carrier door and movable between a first position
remote from said carrier door and adjacent said load
10 lock door and a second position adjacent said load
lock door and remote from said load lock door;

a first actuator for moving said coupling means
between said first and second positions;

15 said coupling means including gripper members movable
between non-gripping positions free of engagement with
said carrier door and gripping positions in gripping
engagement with said carrier door when said coupling
20 means is in said first position; and

a second actuator for moving said gripper members
between the non-gripping positions and the gripping
positions.

25

48. A system as set forth in claim 47

wherein said carrier door has a peripheral rim;

30 wherein said first actuator includes a drive rod for
moving said coupling means between said first and
second positions;

wherein said coupling means includes a coupler frame
35 mounted on said drive rod; and

wherein said gripper members include opposed axially

aligned gripper rods supported on and guided by said coupler frame for movement between the non-gripping positions and the gripping positions, each said gripper member having a transverse gripper finger at its terminal end, said gripper fingers being engaged with said peripheral rim when said gripper members are in their gripping positions.

49. A system as set forth in claim 47 including:

a load lock door drive mechanism for moving said load lock door between the closed and open positions.

50. A system as set forth in claim 49 including:

a load lock door drive mechanism for moving said load lock door between the closed position coextensive with said load lock port and an open position distant therefrom, and for simultaneously moving as a unit with said load lock door said coupling means and said carrier door integral therewith upon movement of said gripper members to their gripping positions in engagement with said rim of said carrier door and upon movement of said coupling means to the first position.

51. A system for batch loading semiconductor wafers comprising:

a portable carrier for supporting and transporting in a substantially particle free environment a plurality of the wafers in spaced generally stacked relationship, said carrier having a carrier port for providing access to the interior thereof;

a carrier door on said carrier movable between a closed position overlying said carrier port for

sealing the interior of said carrier from the surrounding atmosphere and an open position spaced from said carrier port;

5 a transport chamber for receiving wafers for transfer to a plurality of processing stations;

10 a load lock defining a chamber therein having a substantially particle free environment and including a load lock port opening into the load lock chamber, said load lock positioned intermediate said carrier and said transport chamber;

15 a load lock door on said load lock movable between a closed position overlying said load lock port and an open position spaced therefrom;

20 a load lock arm within the load lock chamber movable between an inactive position distant from said carrier and an active position proximate said carrier;

25 a multilevel end effector on said load lock arm for moving the plurality of wafers as a grouping between said carrier and the load lock chamber; and

30 a transport arm within said transport chamber for retrieving wafers one at a time from said multilevel end effector and delivering it to a specified one of a plurality of processing stations.

52. A system as set forth in claim 51 including:

35 a coordinated door opening drive mechanism for sequentially opening said carrier door and said load lock door when said arm is in the active position.

53. A system as set forth in claim 51 including:

housing means for sealingly isolating the load lock chamber and the interior of the carrier from the surrounding atmosphere; and

- 5 latching means for releasably sealingly attaching said carrier to said housing.

AMENDED CLAIMS

[received by the International Bureau on 28 october 1996 (28.10.96);
original claims 1,2,5,8-13,21,24,25,29,30,32,34,35,47 and 52 amended;
remaining claims unchanged (23 pages)]

1. In combination with a system for batch loading semiconductor wafers including a portable carrier for supporting and transporting in a substantially particle free environment a plurality of the wafers in spaced generally stacked relationship, said carrier having a carrier port for providing access to the interior thereof, said system including a load lock defining a chamber therein having a substantially particle free environment and including a load lock port opening into the load lock chamber, and an isolation housing for sealingly isolating the load lock chamber and the interior of the carrier from the surrounding atmosphere, a communication access assembly comprising:

a carrier door on said carrier movable between a closed position overlying said carrier port for sealing the interior of said carrier from the surrounding atmosphere and an open position spaced from said carrier port;

a load lock door on said load lock movable between a closed position overlying said load lock port for sealing the load lock chamber from the surrounding atmosphere and an open position spaced therefrom;

a carrier door drive mechanism on said load lock door for moving said carrier door between the closed and open positions;

said isolation housing having an aperture generally aligned with said load lock port but spaced therefrom and including a platform for supporting said carrier thereon such that said carrier port is proximate the aperture in said isolation housing; and

AMENDED SHEET (ARTICLE 19)

seal means between said isolation housing and said carrier when said carrier is supported on said platform and encompassing said carrier port and the aperture in said isolation housing for isolating the interior of said carrier, the interior of said isolation housing and the load lock chamber from the surrounding atmosphere.

2. The combination as set forth in claim 1

wherein said carrier door drive mechanism includes:

coupling means selectively engageable with said carrier door and movable between a first position remote from said carrier door and adjacent said load lock door and a second position adjacent said carrier door and remote from said load lock door;

a first actuator for moving said coupling means between said first and second positions;

said coupling means including gripper members movable between non-gripping positions free of engagement with said carrier door and gripping positions in gripping engagement with said carrier door when said coupling means is in said second position; and

a second actuator for moving said gripper members between the non-gripping positions and the gripping positions.

3. The combination as set forth in claim 2

wherein said carrier door has a peripheral rim;

wherein said first actuator includes a drive rod for moving said coupling means between said first and second positions;

wherein said coupling means includes a coupler frame mounted on said drive rod; and

wherein said gripper members include opposed axially aligned gripper rods supported on and guided by said coupler frame for movement between the non-gripping positions and the gripping positions, each said gripper member having a transverse gripper finger at its terminal end, said gripper fingers being engaged with said peripheral rim when said gripper members are in their gripping positions.

4. The combination as set forth in claim 1 including:

a load lock door drive mechanism for moving said load lock door between the closed and open positions.

5. The combination as set forth in claim 3 including:

a load lock door drive mechanism for moving said load lock door between the closed position coextensive with said load lock port and an open position distant therefrom, and for simultaneously moving as a unit with said load lock door said coupling means and said carrier door integral therewith upon movement of said gripper members to their gripping positions in engagement with said rim of said carrier door and upon movement of said coupling means to said second position.

6. The combination as set forth in claim 2 including:

wherein said carrier door is recessed and has a gripper slot therein;

wherein said first actuator includes a drive rod for moving said coupling means between said first and second positions;

wherein said coupling means includes:

a door gripper plate mounted on said drive rod and matingly receivable with said carrier port when said coupling means is in the second position; and

a door gripper bar on said second actuator and having pair of bent fingers at a distal end thereof movable between a gripping position grippingly engaging the gripper slot in said carrier door and a release position disengaged therefrom.

7. The combination as set forth in claim 6 including:

latch means on said carrier door selectively engageable with said carrier for securely attaching said carrier door to said carrier.

8. The combination as set forth in claim 7

wherein said carrier has a latch recess in said carrier port;

wherein said latch means includes:

a latch pivotally mounted on said carrier door for movement between a latching position engaged with said latch recess and an unlatching position disengaged from said latch recess;

a retention pin pivotally connected to said latch having a first end within said carrier door and having a second turned end opposite said first end, said

AMENDED SHEET (ARTICLE 19)

turned end receivable between said pair of bent fingers and engageable with said door gripper bar; and

resilient means biasing said latch to the latching position;

whereby movement of said door gripper bar to move said pair of bent fingers into the gripping position grippingly engaging the gripper slot in said carrier door is effective to simultaneously move said latch to the unlatching position disengaged from said latch recess.

9. The combination as set forth in claim 8 including:

a load lock door drive mechanism for moving said load lock door between the closed position coextensive with said load lock port and an open position distant therefrom, and for simultaneously moving as a unit with said load lock door said coupling means and said carrier door integral therewith upon movement of said gripper members to their gripping positions in engagement with said rim of said carrier door and upon movement of said coupling means to the first position.

10. A system for batch loading semiconductor wafers comprising:

a portable carrier for supporting and transporting in a substantially particle free environment a plurality of the wafers in spaced generally stacked relationship, said carrier having a carrier port for providing access to the interior thereof;

a load lock defining a chamber therein having a substantially particle free environment and including

AMENDED SHEET (ARTICLE 19)

a load lock port opening into the load lock chamber;

means for sealingly isolating the load lock chamber and the interior of the carrier from the surrounding atmosphere;

a load lock arm within the load lock chamber movable between an inactive position distant from said carrier and an active position proximate said carrier; and

a multilevel end effector on said load lock arm including a plurality of spaced end effector sets, each said end effector set adapted to support a wafer thereon, each of said plurality of spaced end effector sets being aligned with an associated wafer supported in the carrier when said load lock arm is in the active position, said multilevel end effector being movable from a retracted position distant from the wafers to an advanced position extending through said load lock port and through said carrier port into the carrier for engaging and simultaneously retrieving the wafers as a grouping, then again to the retracted position, holding the grouping of wafers in the load lock chamber.

11. A system for batch loading semiconductor wafers comprising:

a portable carrier for supporting and transporting in a substantially particle free environment a plurality of the wafers in substantially spaced relationship, said carrier having a carrier port for providing access to the interior thereof;

a carrier door on said carrier movable between a closed position overlying said carrier port for sealing the interior of said carrier from the surrounding environment and an open position spaced

AMENDED SHEET (ARTICLE 19)

from said carrier port;

a load lock defining a chamber therein having a substantially particle free environment and including a load lock port opening into the load lock chamber;

a load lock door on said load lock movable between a closed position overlying said load lock port and an open position spaced therefrom;

a load lock arm within the load lock chamber movable between an inactive position distant from the carrier and an active position proximate the carrier; and

a multilevel end effector on said load lock arm including a plurality of spaced end effector sets, each said end effector set adapted to support a wafer thereon, each of said plurality of spaced end effector sets being aligned with an associated wafer supported in the carrier when said load lock arm is in the active position, said multilevel end effector being movable, when said load lock arm is in the active position and when said load lock door is in the open position, from a retracted position distant from the wafers to an advanced position within the carrier and extending through said load port and through said carrier port for engaging and simultaneously retrieving the wafers as a grouping, then again to the retracted position for holding the grouping of the wafers in the load lock chamber.

12. A system as set forth in claim 11

wherein said carrier has a plurality of spaced rack member sets for supporting the wafers, each of said plurality of spaced end effector sets being aligned with an associated one of said rack member sets when said load lock arm is in the active position.

AMENDED SHEET (ARTICLE 19)

13. A system as set forth in claim 12

wherein each said end effector set is positioned for generally horizontally supporting a wafer thereon; and

wherein said plurality of said rack member sets in said carrier are vertically spaced for reception of the wafers thereon in a stacked relationship.

14. A system as set forth in claim 11

including:

an arm drive mechanism for moving said load lock arm between the inactive position and the active position; and

an end effector drive mechanism for moving said multilevel end effector between the retracted and advanced positions.

15. A system as set forth in claim 11 including:

a load lock door drive mechanism for moving said load lock door between the closed and open positions.

16. A system as set forth in claim 11 including:

a carrier door drive mechanism on said load lock door for moving said carrier door between the closed and open positions when said load lock door is in the closed position.

17. A system as set forth in claim 14 including:

a load lock door drive mechanism for moving said load lock door between the closed and open positions; and

AMENDED SHEET (ARTICLE 19)

a carrier door drive mechanism on said load lock door for moving said carrier door between the closed and open positions when said load lock door is in the closed position.

18. A system as set forth in claim 11 including:

an isolation housing for sealingly isolating the load lock chamber and the interior of the carrier from the surrounding atmosphere.

19. A system as set forth in claim 18

wherein said isolation housing has an aperture generally aligned with said load lock port but spaced therefrom and includes a platform for supporting said carrier thereon such that said carrier port is proximate the aperture in said isolation housing; and

including:

seal means between said isolation housing and said carrier when supported on said platform and encompassing said carrier port and the aperture in said isolation housing for isolating the interior of said carrier, the interior of said isolation housing and the load lock chamber from the surrounding atmosphere.

20. A system as set forth in claim 11 including:

seal means between said load lock door and said load lock for isolating the load lock chamber from the atmosphere when said load lock door is in the closed position.

21. A system for batch loading semiconductor wafers comprising:

AMENDED SHEET (ARTICLE 19)

a portable carrier for supporting and transporting a plurality of the wafers in spaced substantially spaced relationship, said carrier having a carrier port for providing access to the interior thereof;

a carrier door on said carrier movable between a closed position overlying said carrier port and an open position spaced from said carrier port;

a load lock defining a chamber therein and including a load lock port opening into the load lock chamber;

a load lock door on said load lock movable between a closed position overlying said load lock port and an open position spaced therefrom;

a load lock arm within the load lock chamber movable between an inactive position distant from the carrier and an active position proximate the carrier;

a multilevel end effector on said arm for moving the plurality of wafers as a grouping between said carrier and the load lock chamber; and

a coordinated door opening drive mechanism for sequentially opening said carrier door and said load lock door when said arm is in the active position;

wherein said multilevel end effector includes a plurality of spaced end effector sets, each said end effector set adapted to support a semiconductor wafer thereon, each of said plurality of spaced end effector sets being aligned with an associated wafer supported in said carrier when said arm is in the active position, said multilevel end effector being movable, when said arm is in the active position, from a retracted position distant from the wafers to an advanced position within the carrier for engaging and

simultaneously retrieving the wafers as a grouping, then again to the retracted position while holding the grouping of wafers and, when said arm is in the inactive position, each of said plurality of spaced end effector sets being out of alignment with an associated wafer supported in said carrier and said multilevel end effector being incapable of movement when said arm is in the inactive position.

22. A system as set forth in claim 21

wherein said multilevel end effector includes a plurality of spaced end effector sets, each said end effector set adapted to support a semiconductor wafer thereon, each of said plurality of spaced end effector sets being aligned with an associated wafer supported in said carrier when said arm is in the active position, said multilevel end effector being movable, when said arm is in the active position, from a retracted position distant from the wafers to an advanced position within said carrier for engaging and simultaneously retrieving the wafers as a grouping, then again to the retracted position while holding the grouping of wafers and, when said arm is in the inactive position, each of said plurality of spaced end effector sets being out of alignment with an associated wafer supported in said carrier and said multilevel end effector being incapable of movement when said arm is in the inactive position.

23. A system as set forth in claim 21

wherein said coordinated door opening drive mechanism includes means for sequentially moving said carrier door and said load lock door as a unit from a location generally coextensive with said carrier port and with said load lock port to a location distant therefrom.

24. A system for batch loading semiconductor wafers to and from a carrier having an interior region used for supporting and transporting in a substantially particle free environment

a plurality of the wafers in spaced generally stacked relationship, said system comprising:

a load lock defining a chamber therein having a substantially particle free environment and including a load lock port opening into the load lock chamber;

a load lock door on said load lock movable between a closed position sealingly overlying said load lock port and an open position spaced therefrom;

a load lock arm within the load lock chamber movable between an inactive position distant from the carrier and an active position proximate the carrier; and

a multilevel end effector on said load lock arm including a plurality of spaced end effector sets, each said end effector set adapted to support a wafer thereon, each of said plurality of spaced end effector sets being aligned with an associated wafer supported in the carrier when said load lock arm is in the active position, said multilevel end effector being movable, when said load lock arm is in the active position and when said load lock door is in the open position, from a retracted position distant from the wafers to an advanced position extending into the interior region of the carrier for engaging and simultaneously retrieving the wafers as a grouping, then again to the retracted position for holding the grouping of wafers in the load lock chamber.

25. A system as set forth in claim 24 including:

an arm drive mechanism for moving said load lock arm between the inactive position and the active position; and

an end effector drive mechanism for moving said multilevel end effector between the retracted and advanced positions.

26. A system as set forth in claim 25 including:

an isolation housing for sealingly isolating the load lock chamber and the interior of the carrier from the surrounding atmosphere.

27. A system as set forth in claim 24 including:

seal means between said load lock door and said load lock for isolating the load lock chamber from the surrounding atmosphere when said load lock door is in the closed position.

28. A system as set forth in claim 24 including:

a load lock door drive mechanism for moving said load lock door between the closed and open positions.

29. A system as set forth in claim 24 including:

vacuum means for selectively evacuating the load lock chamber when said load lock door is in the closed position;

a source of vacuum;

conduit means extending between said source of vacuum and the load lock chamber;

selectively operable valve means in said conduit means

AMENDED SHEET (ARTICLE 19)

for interconnecting said vacuum source and the load lock chamber when the load lock chamber is isolated from the surrounding atmosphere.

30. A system for handling a plurality of semiconductor wafers supported in spaced, generally stacked, relationship comprising:

arm means movable between an active position and an inactive position distant from the active position;

a multilevel end effector on said arm means including a plurality of spaced end effector sets, each said end effector set adapted to support a semiconductor wafer thereon, each of said plurality of spaced end effector sets being aligned with an associated wafer supported within an interior region of a carrier when said arm means is in the active position, said multilevel end effector being movable, when said arm means is in the active position, from a retracted position distant from the wafers to an advanced position extending into the interior region of the carrier for engaging and simultaneously retrieving the wafers as a grouping, then again to the retracted position while holding the grouping of wafers and, when said arm means is in the inactive position, each of said plurality of spaced end effector sets being out of alignment with an associated wafer supported in a carrier and said multilevel end effector being incapable of movement when said arm means is in the inactive position.

31. A system for handling semiconductor wafers as set forth in claim 30 including:

arm drive means for moving said arm means between the active position and the inactive position.

32. A system for handling semiconductor wafers

AMENDED SHEET (ARTICLE 19)

as set forth in claim 31

wherein said arm drive means includes index drive means for incrementally moving said multilevel end effector in order to locate a selected one of said plurality of end effector sets at a predetermined position for removal therefrom of the individual wafer supported thereon.

33. A system for batch loading semiconductor wafers comprising:

a portable carrier for supporting and transporting in a substantially particle free environment a plurality of the wafers in spaced generally stacked relationship, said carrier having a carrier port for providing access to the interior thereof;

a plurality of rack members for supporting a plurality of the wafers in spaced relationship within said carrier;

a carrier door on said carrier movable between a closed position overlying said carrier port for sealing the interior of said carrier from the surrounding atmosphere and an open position spaced from said carrier port;

a transport chamber for receiving wafers for transfer to a plurality of processing stations;

a load lock defining a chamber therein having a substantially particle free environment and including a load lock port opening into the load lock chamber, said load lock positioned intermediate said carrier and said transport chamber;

a load lock door on said load lock movable between a

AMENDED SHEET (ARTICLE 19)

closed position overlying said load lock port and an open position spaced therefrom;

a load lock arm within the load lock chamber movable between an inactive position distant from said carrier and an active position proximate said carrier;

a multilevel end effector on said load lock arm including a plurality of spaced end effector sets, each said end effector set adapted to support a wafer thereon, each of said plurality of spaced end effector sets being aligned with an associated wafer supported in said carrier when said load lock arm is in the active position, said multilevel end effector being movable, when said load lock arm is in the active position, from a retracted position distant from the wafers to an advanced position within said carrier and extending through said load port and through said carrier port for engaging and simultaneously retrieving the wafers as a grouping, then again to the retracted position for holding the grouping of wafers in the load lock chamber; and

a transport arm within said transport chamber for retrieving wafers one at a time from said multilevel end effector and delivering it to a specified one of the plurality of processing stations.

34. A system as set forth in claim 33

wherein said carrier has a plurality of spaced rack member sets for supporting the wafers, each of said plurality of spaced end effector sets being aligned with an associated one of said rack member sets when said load lock arm is in the active position.

35. A system as set forth in claim 34

AMENDED SHEET (ARTICLE 19)

wherein each said end effector set is positioned for horizontally supporting a wafer thereon; and

wherein said plurality of said rack member sets in said carrier are vertically spaced for reception of the wafers thereon in a stacked relationship.

36. A system as set forth in claim 33

including:

an arm drive mechanism for moving said load lock arm between the inactive position and the active position; and

an end effector drive mechanism for moving said multilevel end effector between the retracted and advanced positions.

37. A system as set forth in claim 33 including:

a load lock door drive mechanism for moving said load lock door between the closed and open positions.

38. A system as set forth in claim 33 including:

a carrier door drive mechanism on said load lock door for moving said carrier door between the closed and open positions when said load lock door is in the closed position.

39. A system as set forth in claim 36 including:

a load lock door drive mechanism for moving said load lock door between the closed and open positions; and

a carrier door drive mechanism on said load lock door for moving said carrier door between the closed and

AMENDED SHEET (ARTICLE 19)

open positions when said load lock door is in the closed position.

40. A system as set forth in claim 33 including:

an isolation housing for sealingly isolating the load lock chamber and the interior of the carrier from the surrounding atmosphere.

41. A system as set forth in claim 40

wherein said isolation housing has an aperture generally aligned with said load lock port but spaced therefrom and includes a platform for supporting said carrier thereon such that said carrier port is proximate the aperture in said isolation housing; and

including:

seal means between said isolation housing and said carrier when supported on said platform and encompassing said carrier port and the aperture in said isolation housing for isolating the interior of said carrier, the interior of said isolation housing and the load lock chamber from the surrounding atmosphere.

42. A system as set forth in claim 33 including:

seal means between said load lock door and said load lock for isolating the load lock chamber from the atmosphere when said load lock door is in the closed position.

43. A system as set forth in claim 33 including:

seal means between said load lock door and said load lock for isolating the load lock chamber from the

AMENDED SHEET (ARTICLE 19)

surrounding atmosphere when said load lock door is in the closed position.

44. A system as set forth in claim 33 including:

isolation valve means intermediate the load lock chamber and said transport chamber selectively operable to permit fluid intercommunication therebetween in one instance and to prevent fluid intercommunication therebetween in another instance; and

seal means between said load lock and said transfer chamber for isolating said load lock and said transfer chamber from the surrounding atmosphere when said isolation valve means is positioned to permit fluid intercommunication between the load lock chamber and said transfer chamber.

45. A system as set forth in claim 33 including:

a source of vacuum;

conduit means extending between said source of vacuum and the load lock chamber;

selectively operable valve means in said conduit means for interconnecting said vacuum source and the load lock chamber when said load lock door is closed and for disconnecting said vacuum source from the load lock chamber when said load lock door is open.

46. A system as set forth in claim 33 including:

a source of vacuum;

conduit means extending between said source of vacuum and said transfer chamber;

AMENDED SHEET (ARTICLE 19)

selectively operable valve means in said conduit means for interconnecting said vacuum source and said transfer chamber when said transfer chamber is isolated from the surrounding atmosphere.

47. A system as set forth in claim 38

wherein said carrier door drive mechanism includes:

coupling means selectively engageable with said carrier door and movable between a first position remote from said carrier door and adjacent said load lock door and a second position adjacent said carrier door and remote from said load lock door;

a first actuator for moving said coupling means between said first and second positions;

said coupling means including gripper members movable between non-gripping positions free of engagement with said carrier door and gripping positions in gripping engagement with said carrier door when said coupling means is in said first position; and

a second actuator for moving said gripper members between the non-gripping positions and the gripping positions.

48. A system as set forth in claim 47

wherein said carrier door has a peripheral rim;

wherein said first actuator includes a drive rod for moving said coupling means between said first and second positions;

wherein said coupling means includes a coupler frame mounted on said drive rod; and

AMENDED SHEET (ARTICLE 19)

wherein said gripper members include opposed axially aligned gripper rods supported on and guided by said coupler frame for movement between the non-gripping positions and the gripping positions, each said gripper member having a transverse gripper finger at its terminal end, said gripper fingers being engaged with said peripheral rim when said gripper members are in their gripping positions.

49. A system as set forth in claim 47 including:

a load lock door drive mechanism for moving said load lock door between the closed and open positions.

50. A system as set forth in claim 49 including:

a load lock door drive mechanism for moving said load lock door between the closed position coextensive with said load lock port and an open position distant therefrom, and for simultaneously moving as a unit with said load lock door said coupling means and said carrier door integral therewith upon movement of said gripper members to their gripping positions in engagement with said rim of said carrier door and upon movement of said coupling means to the first position.

51. A system for batch loading semiconductor wafers comprising:

a portable carrier for supporting and transporting in a substantially particle free environment a plurality of the wafers in spaced generally stacked relationship, said carrier having a carrier port for providing access to the interior thereof;

a carrier door on said carrier movable between a closed position overlying said carrier port for

AMENDED SHEET (ARTICLE 19)

sealing the interior of said carrier from the surrounding atmosphere and an open position spaced from said carrier port;

a transport chamber for receiving wafers for transfer to a plurality of processing stations;

a load lock defining a chamber therein having a substantially particle free environment and including a load lock port opening into the load lock chamber, said load lock positioned intermediate said carrier and said transport chamber;

a load lock door on said load lock movable between a closed position overlying said load lock port and an open position spaced therefrom;

a load lock arm within the load lock chamber movable between an inactive position distant from said carrier and an active position proximate said carrier;

a multilevel end effector on said load lock arm for moving the plurality of wafers as a grouping between said carrier and the load lock chamber; and

a transport arm within said transport chamber for retrieving wafers one at a time from said multilevel end effector and delivering it to a specified one of a plurality of processing stations.

52. A system as set forth in claim 51 including:

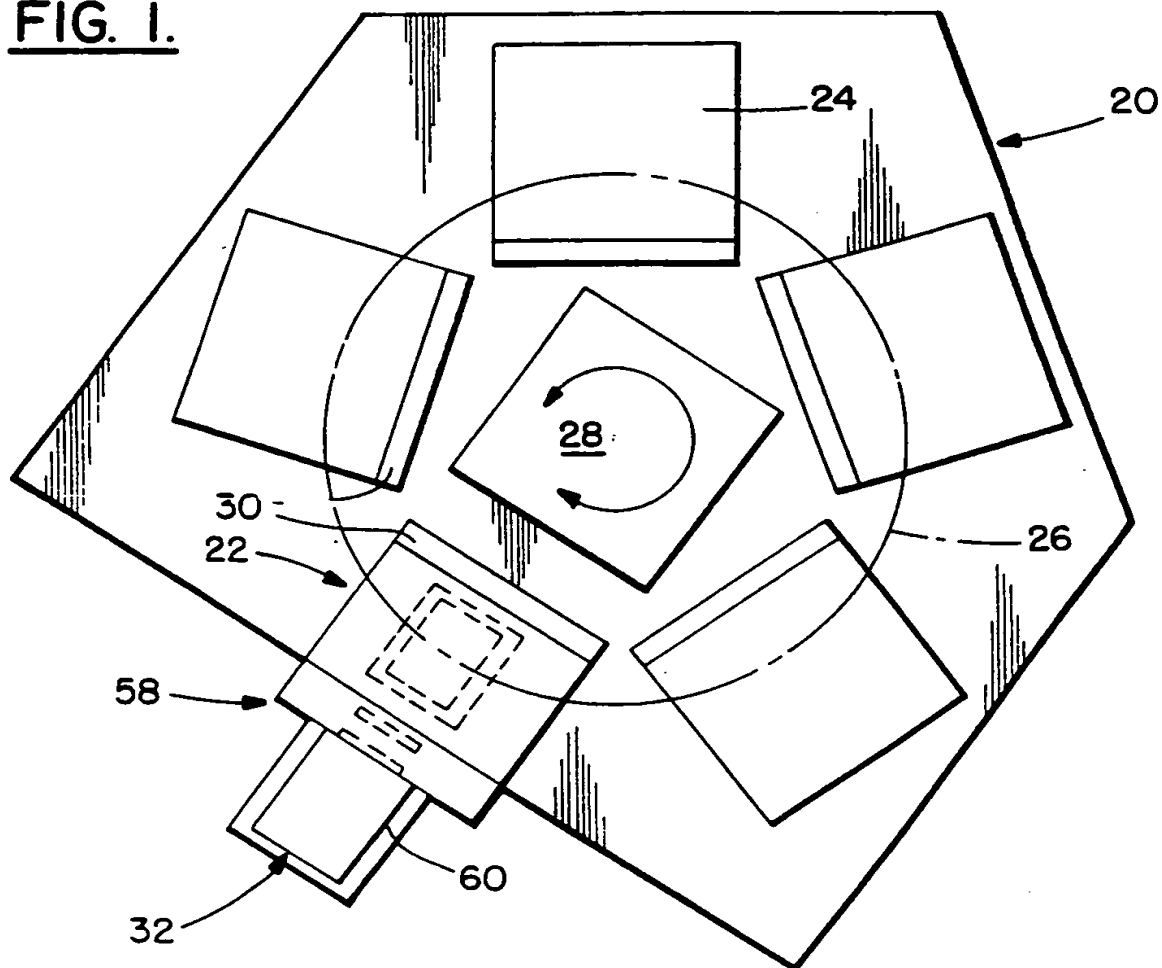
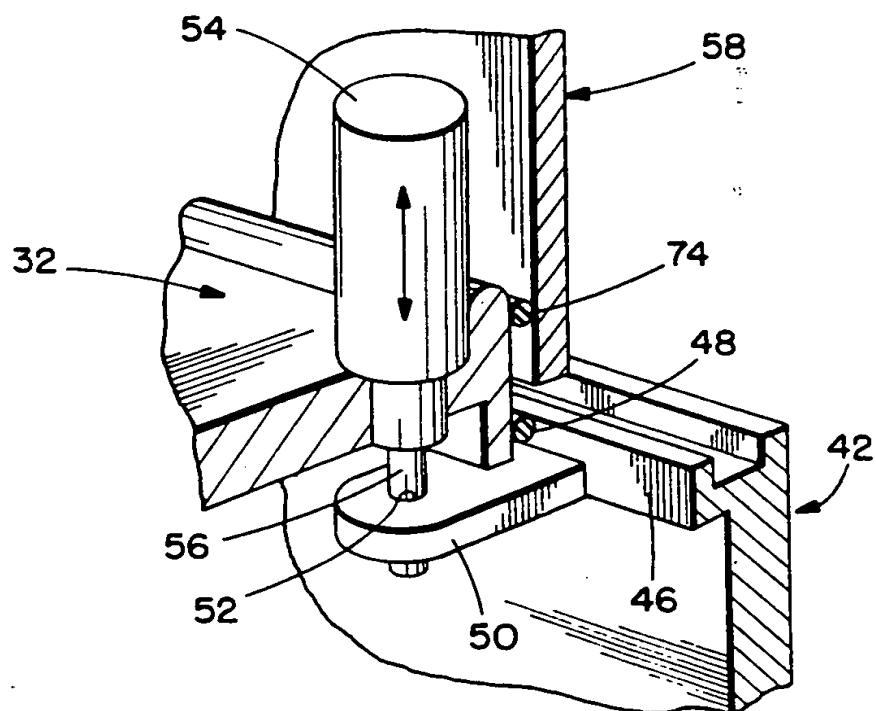
a coordinated door opening drive mechanism for sequentially opening said carrier door and said load lock door when said load lock arm is in the active position.

53. A system as set forth in claim 51 including:

AMENDED SHEET (ARTICLE 19)

housing means for sealingly isolating the load lock chamber and the interior of the carrier from the surrounding atmosphere; and

latching means for releasably sealingly attaching said carrier to said housing.

FIG. 1.FIG. 5.

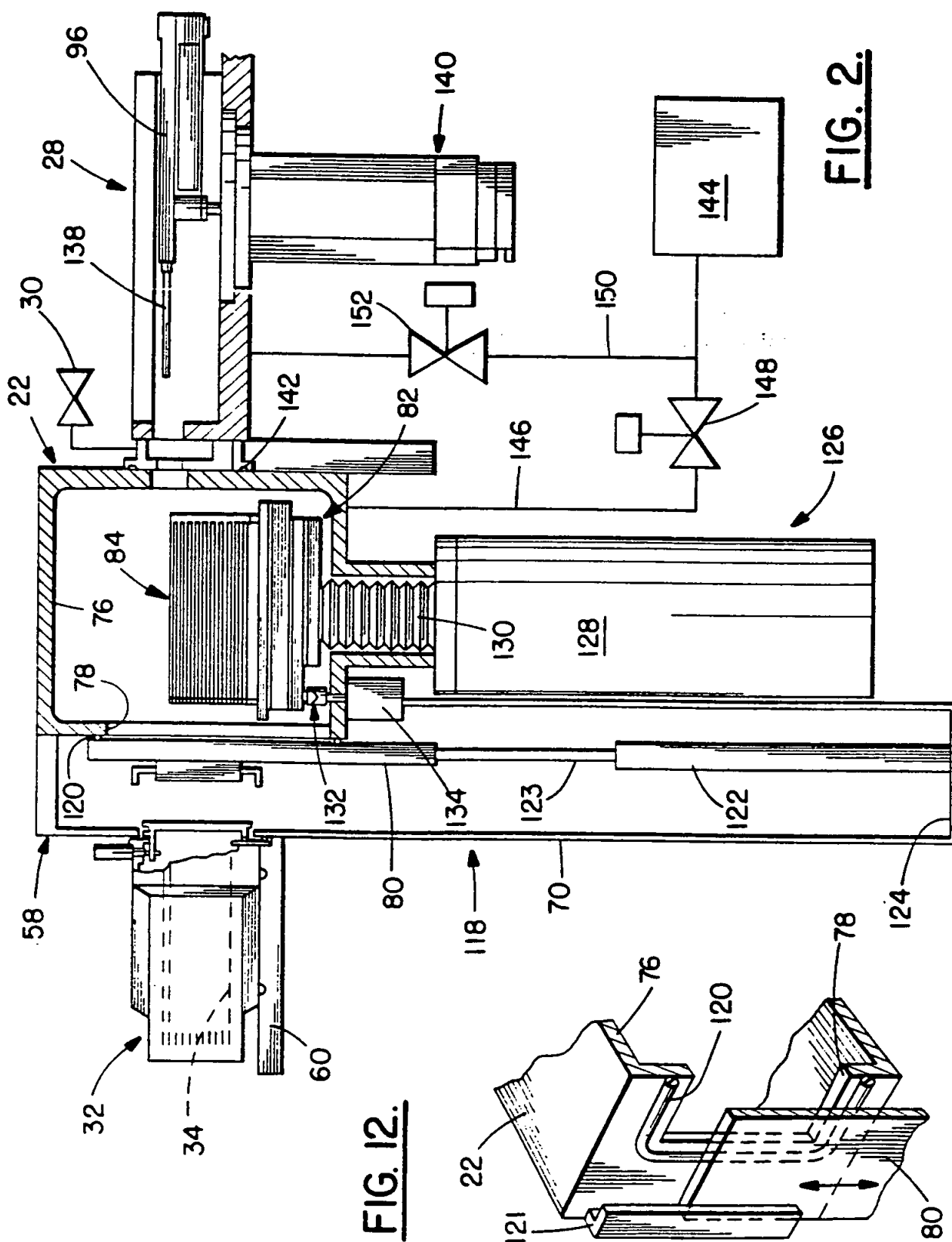
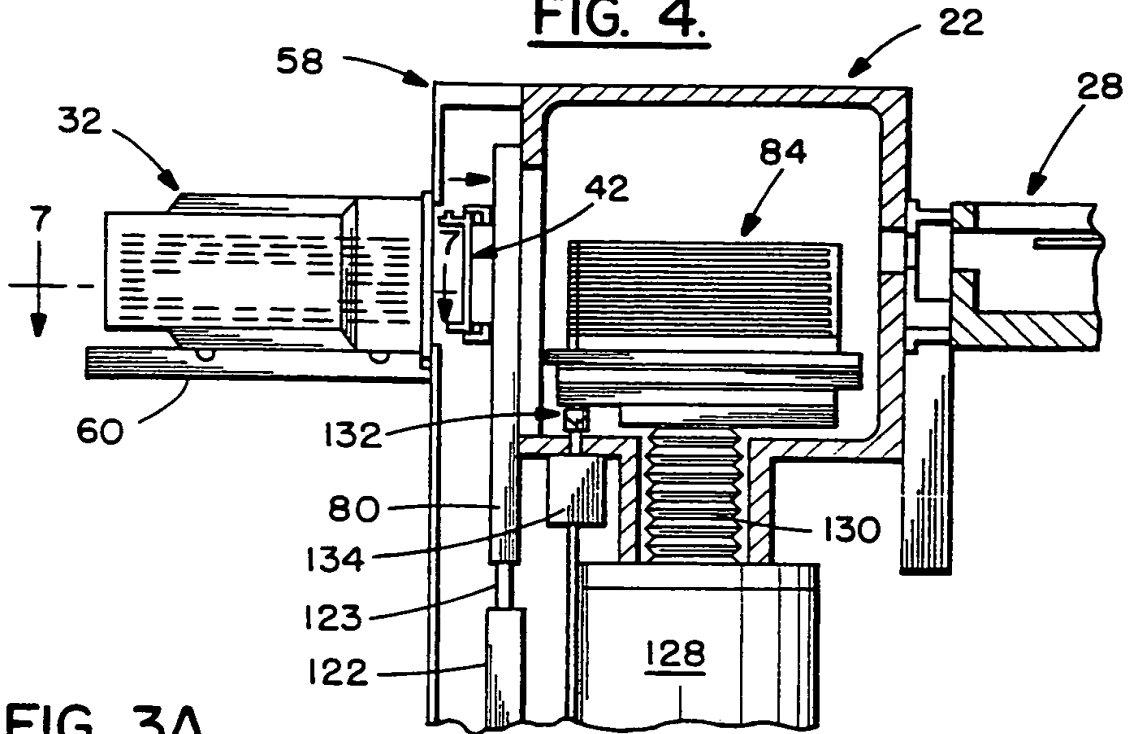
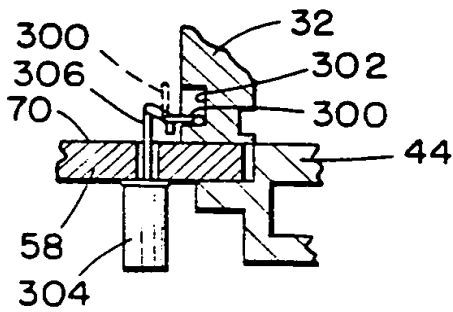
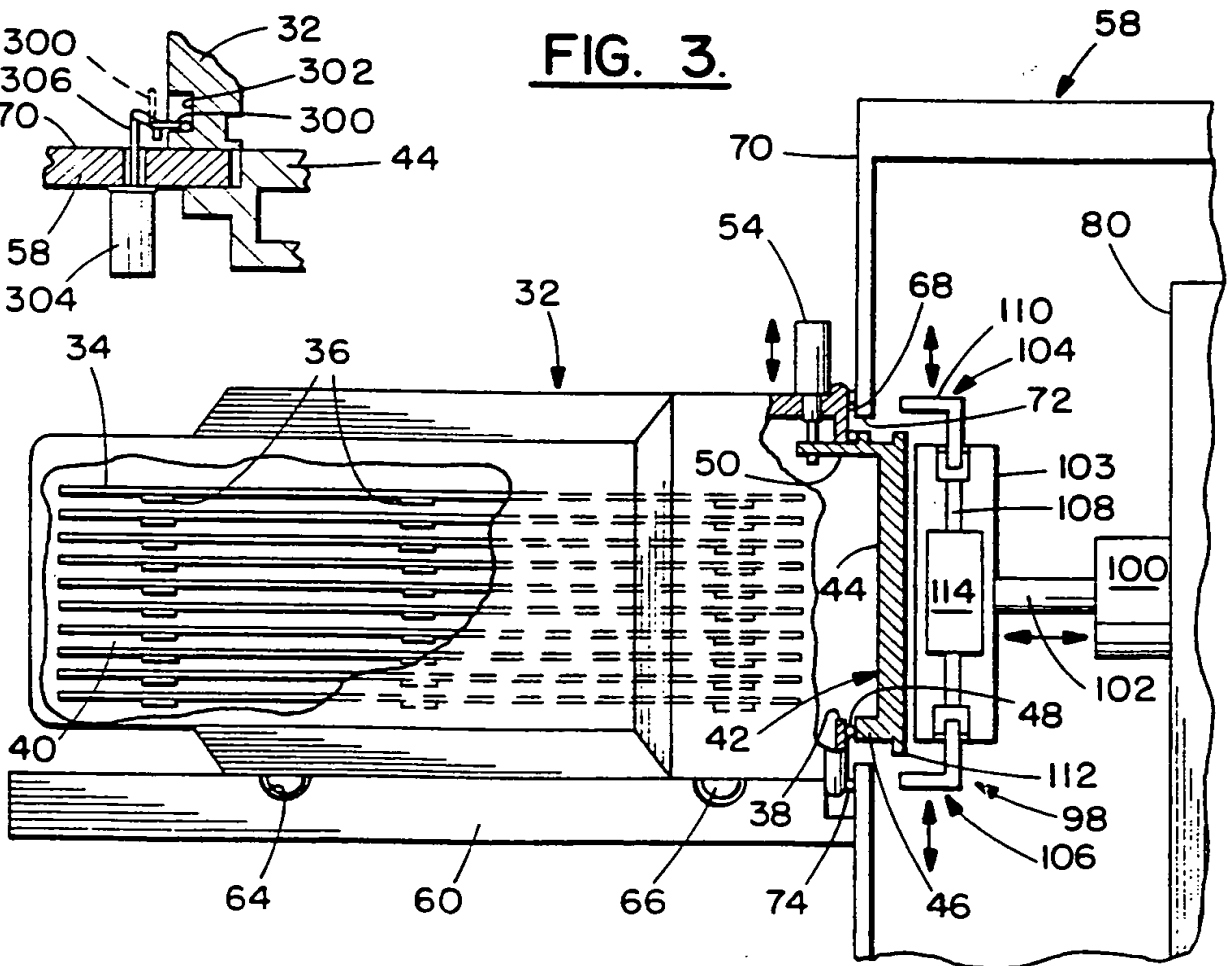


FIG. 4.**FIG. 3A.****FIG. 3.**

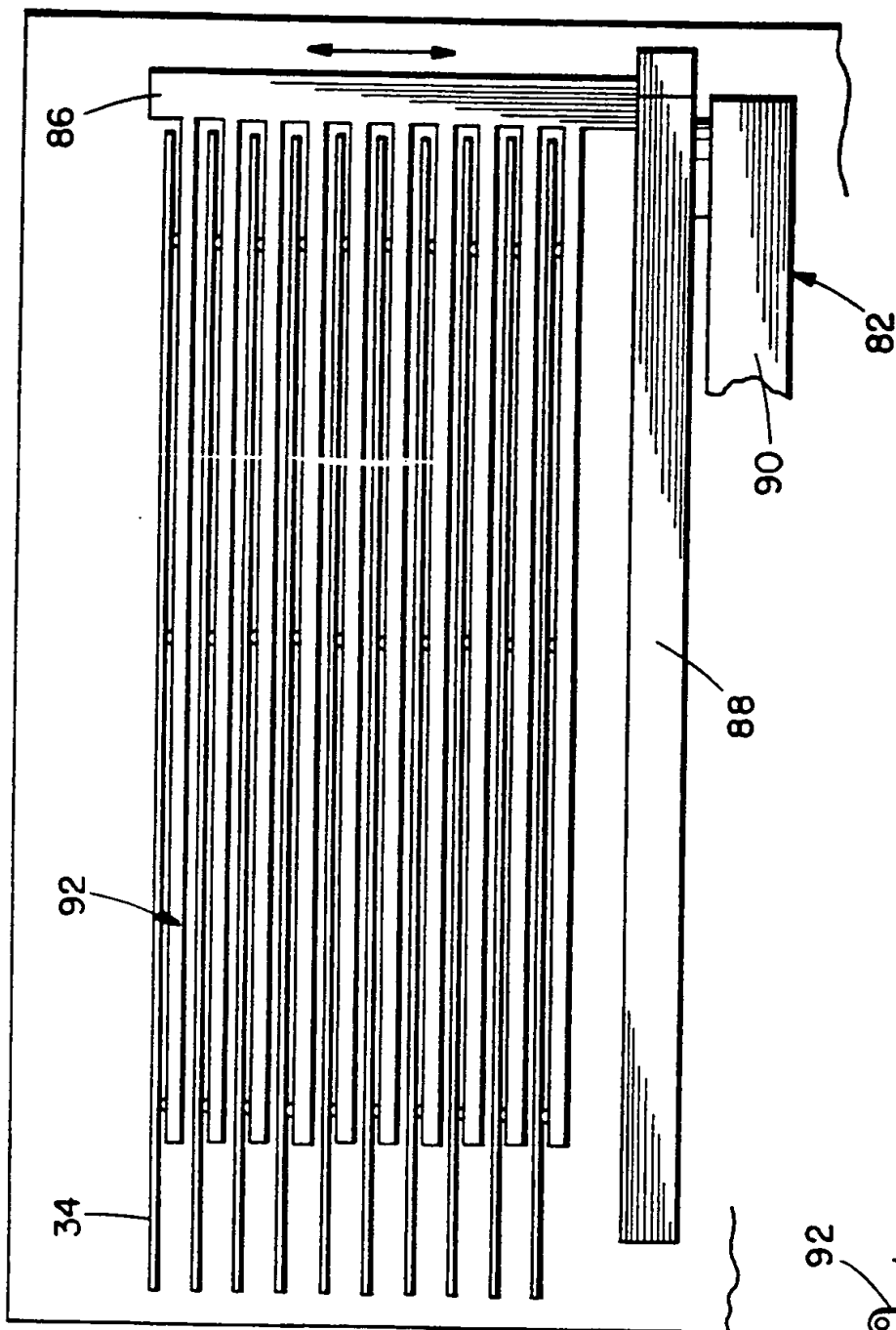


FIG. 6.

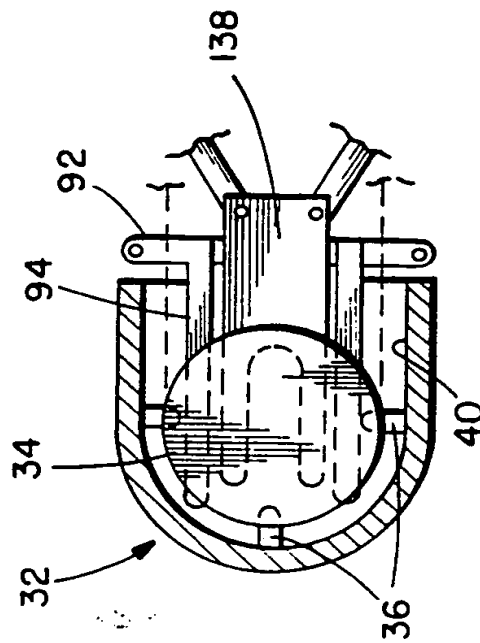


FIG. 7.

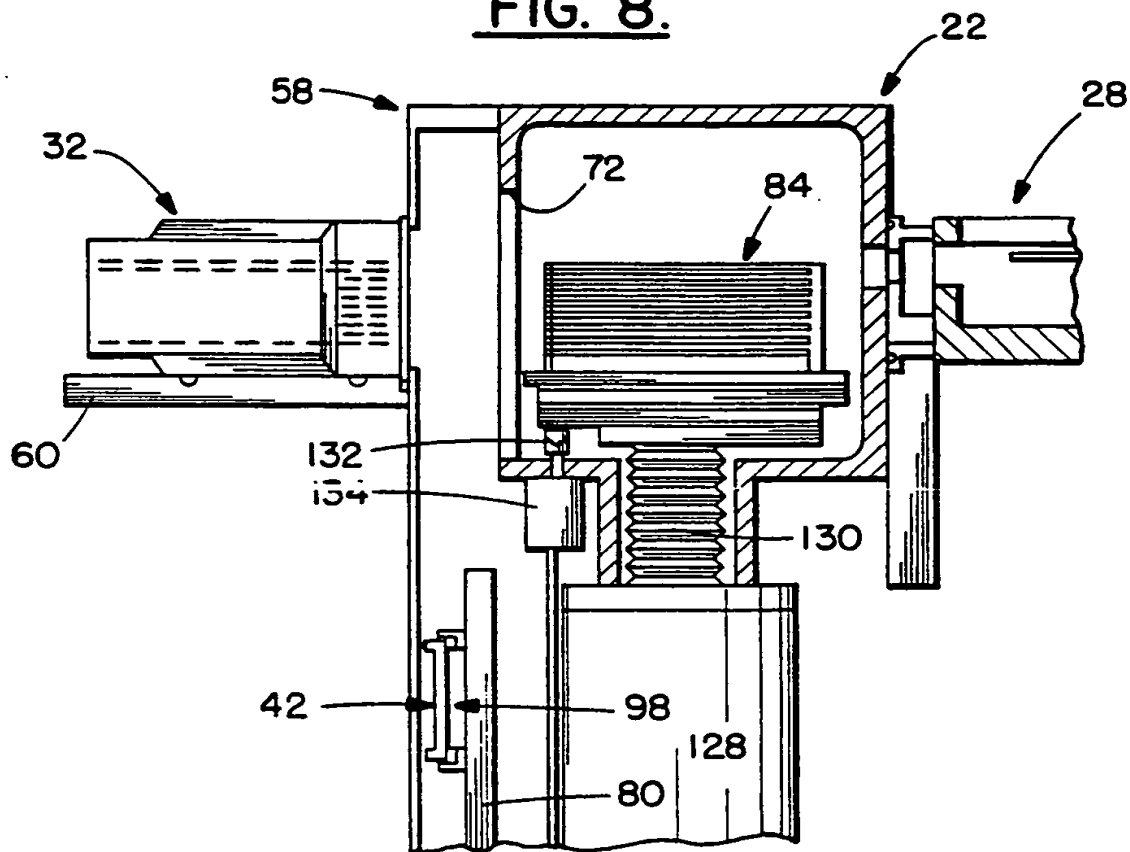
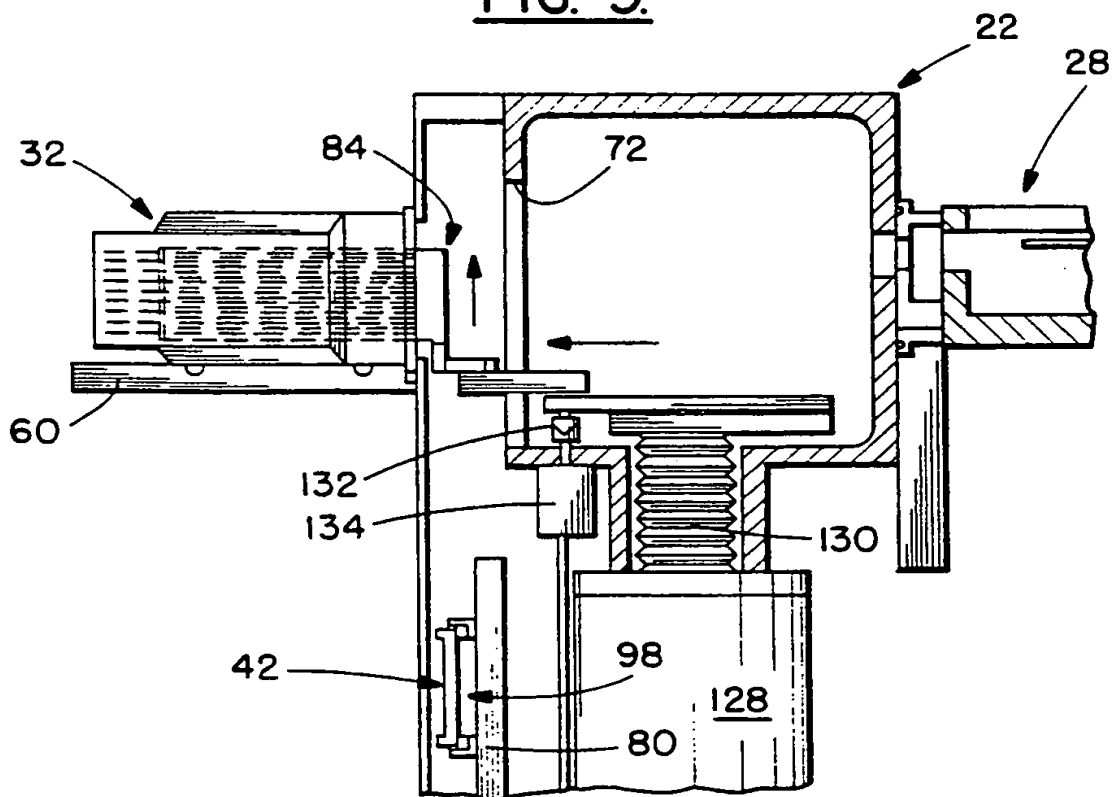
FIG. 8.FIG. 9.

FIG. 10.

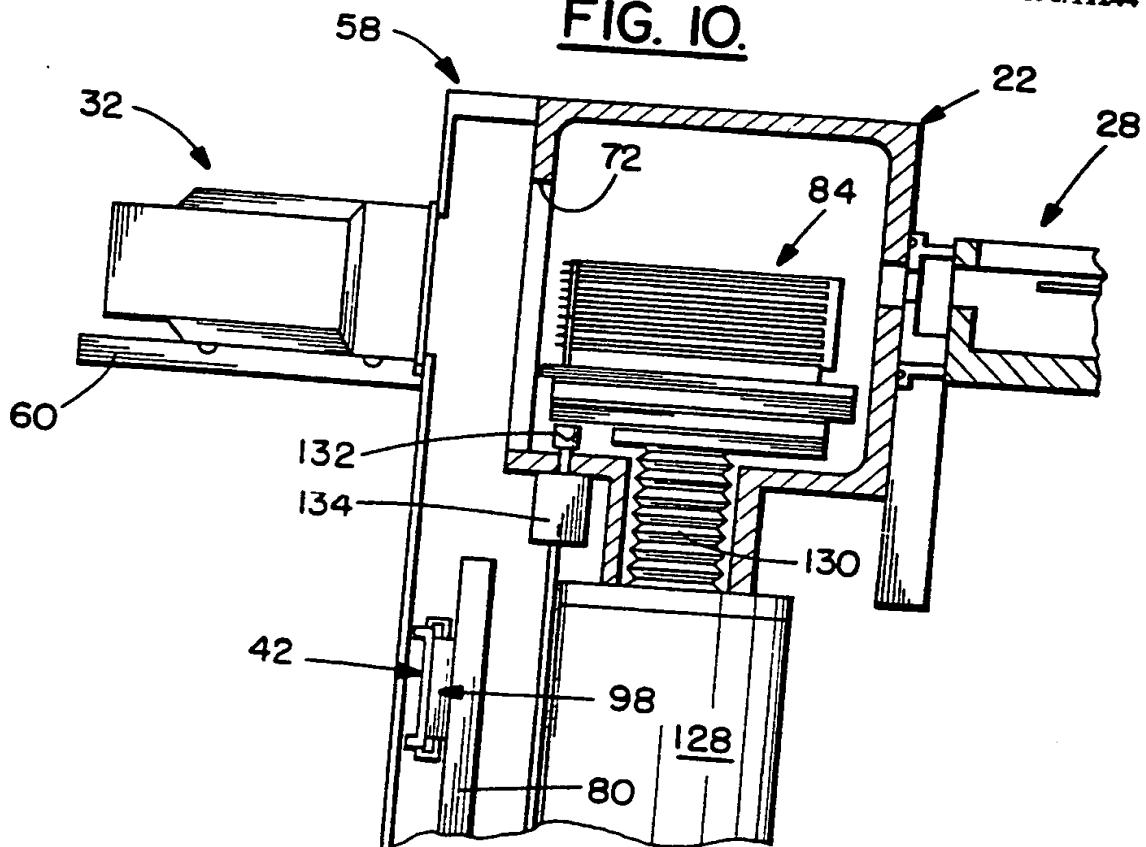


FIG. 11.

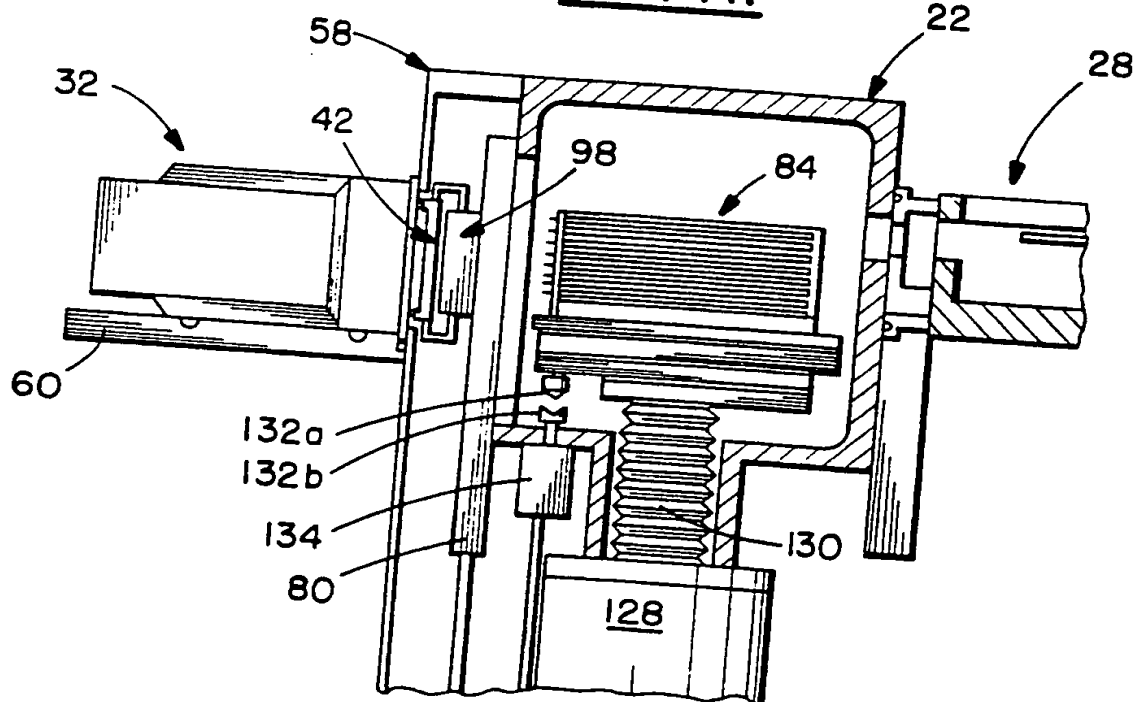


FIG. 13.

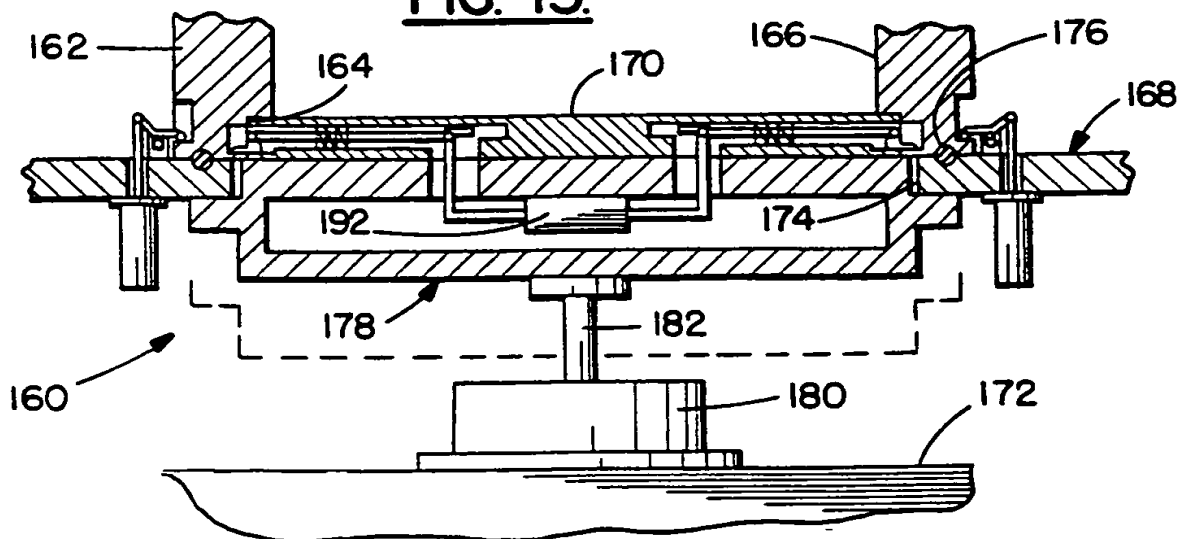


FIG. 14.

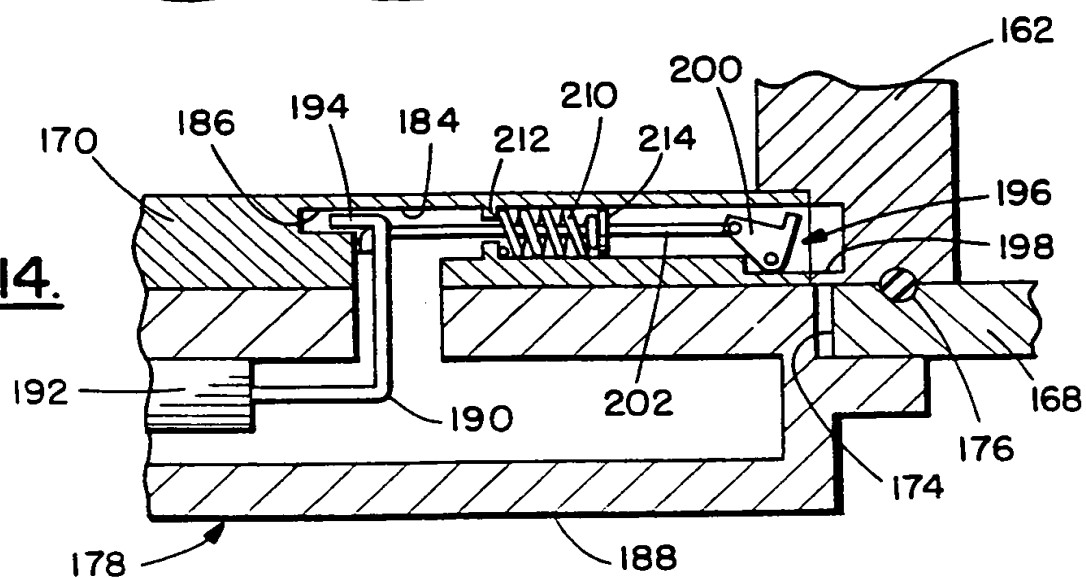
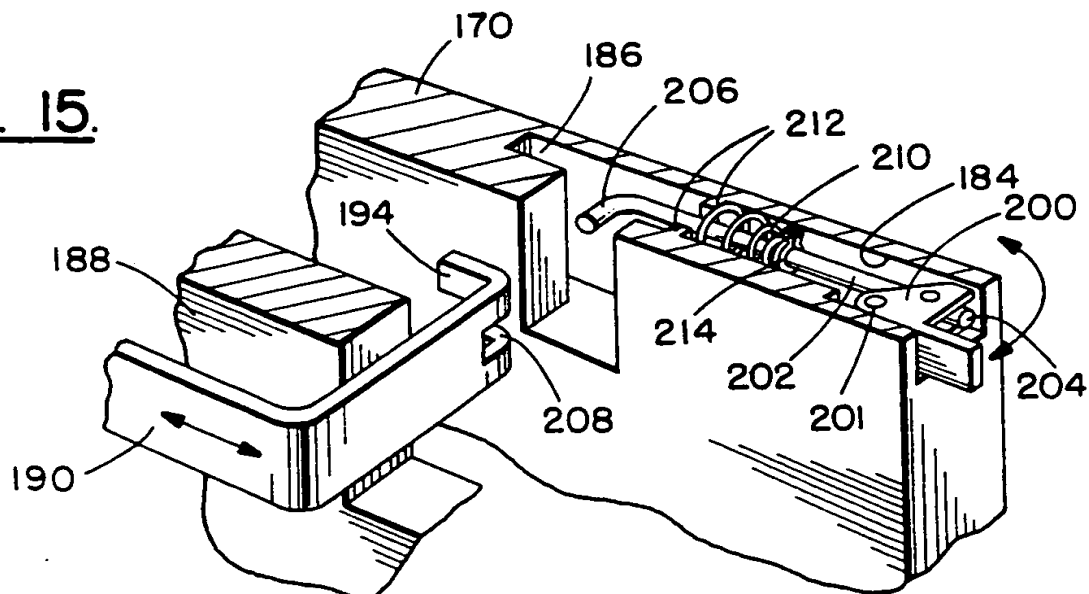


FIG. 15.



INTERNATIONAL SEARCH REPORT

International application No.

PCT/US96/11244

A. CLASSIFICATION OF SUBJECT MATTER

IPC(6) : B65G 49/07

US CL : 414/217

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)

U.S. : 414/217,225,331,416,752,937,939-941

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched
noneElectronic data base consulted during the international search (name of data base and, where practicable, search terms used)
none**C. DOCUMENTS CONSIDERED TO BE RELEVANT**

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
X -- Y	US 5,431,600 A (Murata et al) 11 July 1995, col. 3, line 26 to col. 5, line 19.	21 ---- 21,23, 51-53
Y	JP 4-206547 A (Kitsunai) 28 July 1992, figs. 1 and 4 and constitution.	10,21, 23-32, 51-53
Y	JP 4-61146 A (Yasutake) 27 July 1992, figs. 1-5 and constitution.	10,21,23- 32,51-53
Y	US 4,550,242 A (Uehara et al) 29 October 1985, col. 4, lines 9-30.	10,24-32

☐ Further documents are listed in the continuation of Box C.☐ See patent family annex.

* Special categories of cited documents:	*T* later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention
A document defining the general state of the art which is not considered to be of particular relevance	*X* document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone
E earlier document published on or after the international filing date	*Y* document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being obvious to a person skilled in the art
L document which may throw doubts on priority claim(s) or which is cited to establish the publication date of another citation or other special reason (as specified)	-
O document referring to an oral disclosure, use, exhibition or other means	*G* document member of the same patent family
P document published prior to the international filing date but later than the priority date claimed	

Date of the actual completion of the international search

31 JULY 1996

Date of mailing of the international search report

27 AUG 1996

Name and mailing address of the ISA/US
Commissioner of Patents and Trademarks
Box PCT
Washington, D.C. 20231

Facsimile No. (703) 305-3230

Authorized officer

James Keenan

Telephone No. (703) 308-1113

Form PCT/ISA/210 (second sheet)(July 1992)*

THIS PAGE BLANK (USPTO)